



Status and perspectives of SiPMs

Alberto Gola Chief Scientist

F. Acerbi, A. Ficorella, S. Merzi, L.P. Monreal, E. Moretti, G. Paternoster, M. Penna, M. Ruzzarin, N. Zorzi

Fondazione Bruno Kessler Custom Silicon Photomultipliers

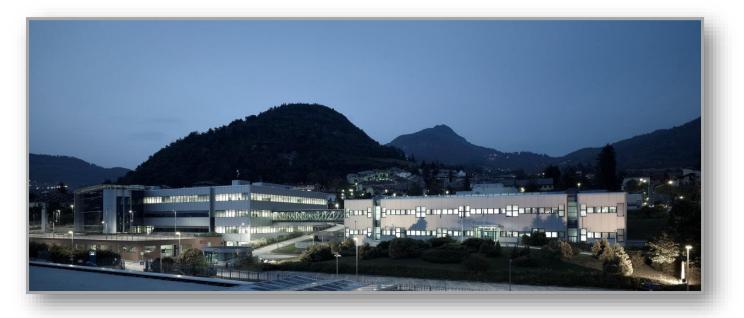


Detector-grade clean-room, 6 inches, class 10 and 100





Silicon Photomultipliers account for a significant portion of the detectors fabricated here.



Private Research Foundation

- ~400 researchers in different fields, ranging from Microelectronics to Information Technology
- 50% funding from local government
- 50% self-funding rate
 - 25% from publicly funded research
 - 25% from collaboration with companies

FBK is typically interested in R&D activities and collaborations to <u>improve and</u> <u>customize SiPM technology for specific applications</u>.

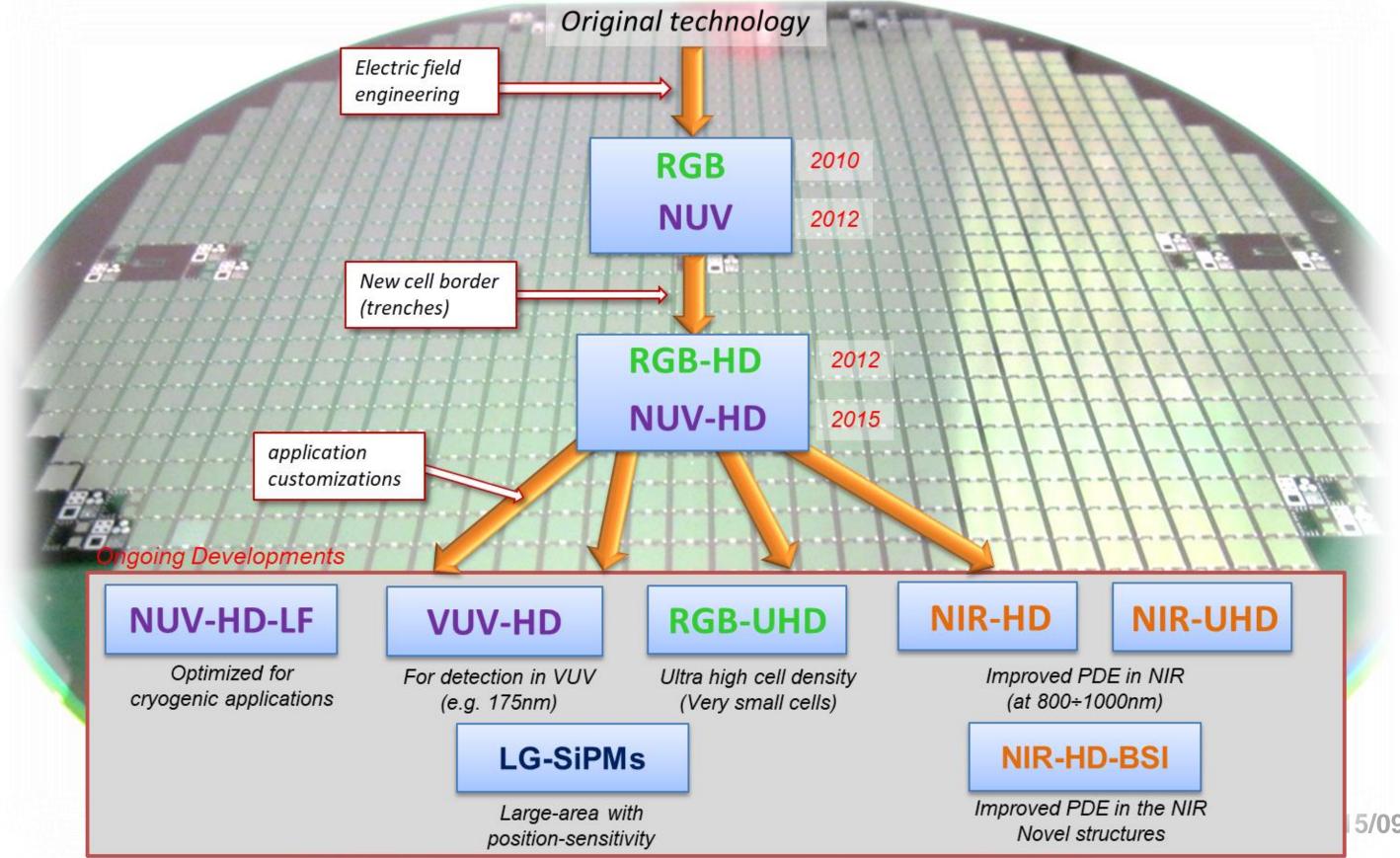
Large area productions can be carried out in FBK (up to ~5 sqm) or relying on external partners (low cost): success stories of technology transfers.







Fondazione Bruno Kessler Custom SiPM technology roadmap

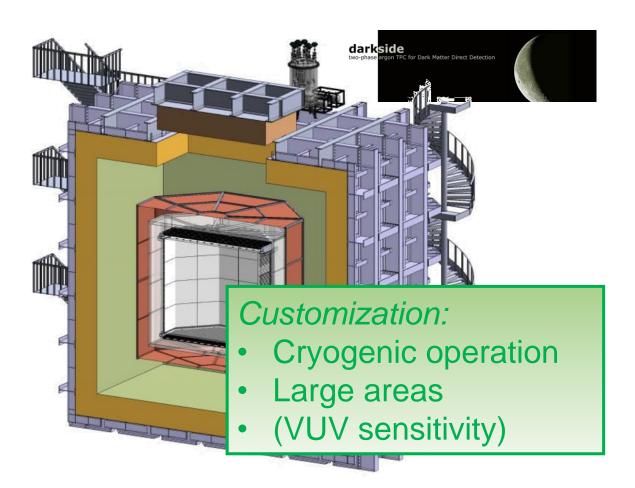




FBK SiPM technologies Use in Big Physics Experiments

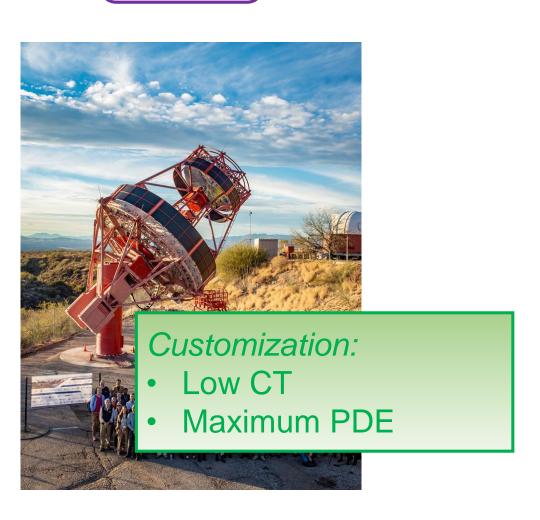
Thanks to constant *performance improvement*, SiPM technologies are now used in several upgrades of Big Physics Experiments: *deep customization is often required*.

Cryogenic TPCs



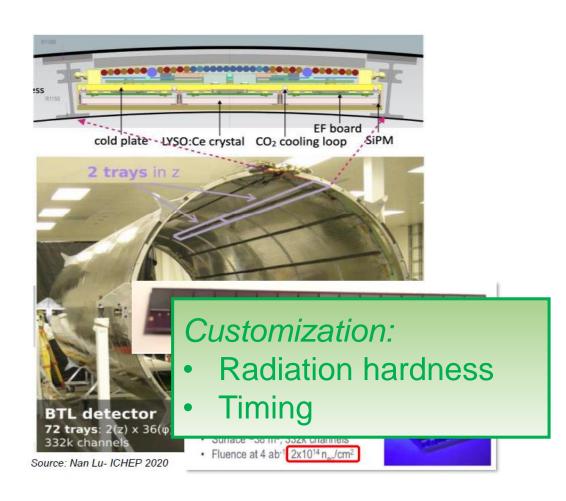
Cryogenic SiPMs will be employed in experiments such as DarkSide-20k

CTA



Prototype pSCT installed in the VERITAS, equipped with FBK SiPMs.

HEP



NUV-HD SiPMs are being evaluated for the MIP timing detector of CMS (LYSO scintillator readout).

FBK SiPM technologies Current R&D activities and Roadmap

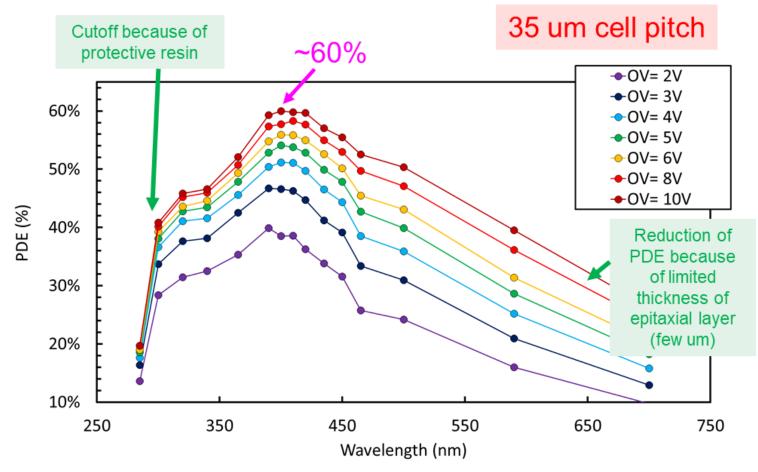
Outline:

- Timing performance
- Reduction of Optical Crosstalk
- Cryogenic operation
- Radiation Hardness
- Light concentration
- Future developments: 2.5 and 3D integration

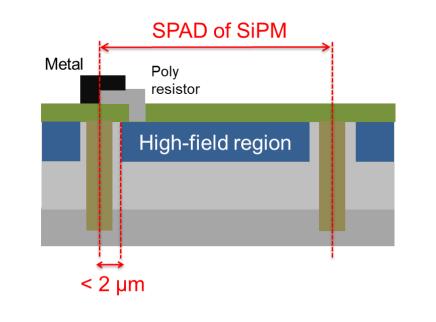


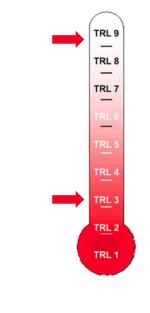
FBK SiPM technologies **NUV-HD SiPM technology**

NUV-HD SiPMs provide state-of-the-art performance for single photon detection, timing and for scintillation light readout.



Gola, A et al. (2019). "NUV-Sensitive Silicon Photomultiplier Technologies Developed at Fondazione Bruno Kessler." Sensors, 19(2), 308.



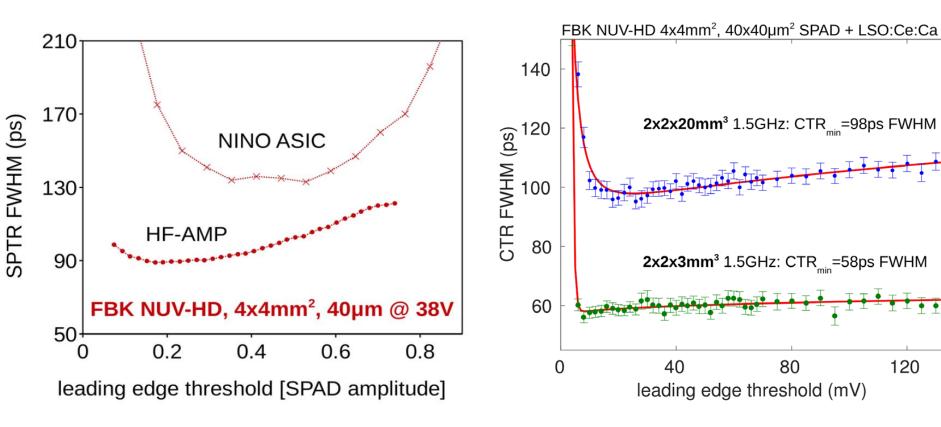












World record timing resolution: Single Photon Time resolution (SPTR, left) and Coincidence Resolving Time (CRT) in LYSO readout (right).

> Gundacker, Stefan, et al. "High-frequency SiPM readout advances measured coincidence time resolution limits in TOF-PET." Physics in Medicine & Biology 64.5 (2019): 055012.



120



SPTR FWHM (ps) vs Laser position (mm)



Timing performance Optimization of SPTR with masking: CHK-HD

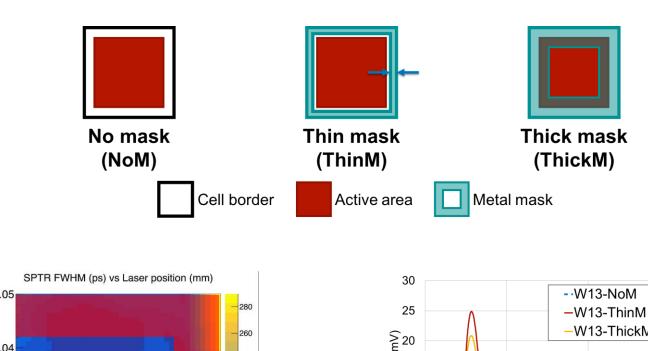
CHK-HD SiPMs is a variant of the NUV-HD SiPMs built to experiment solutions to improve SPTR and detection efficiency in applications where it matters the most, such as Cherenkov light readout.

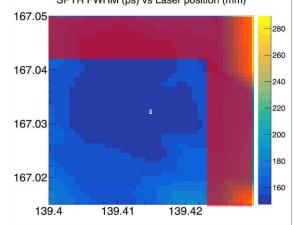
SPTR

180

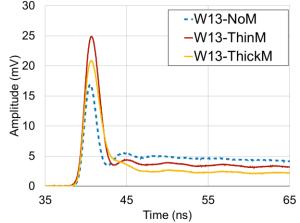
170

- Masking of outer regions of SPAD: Improve signal peaking and mask areas of SPAD with worse SPTR
- Changes to the *Electric field*: low-field + different spectral response





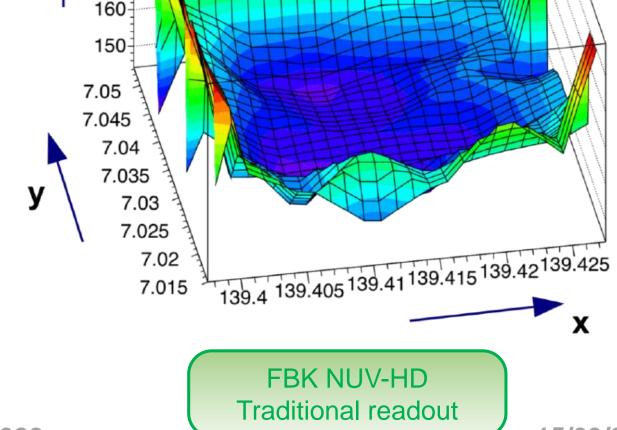
Masking of outer regions of the SPAD that have worse "local" SPTR.



Increase of fast component of single photoelectron signal in accordance with masking extension.



state of 0016.



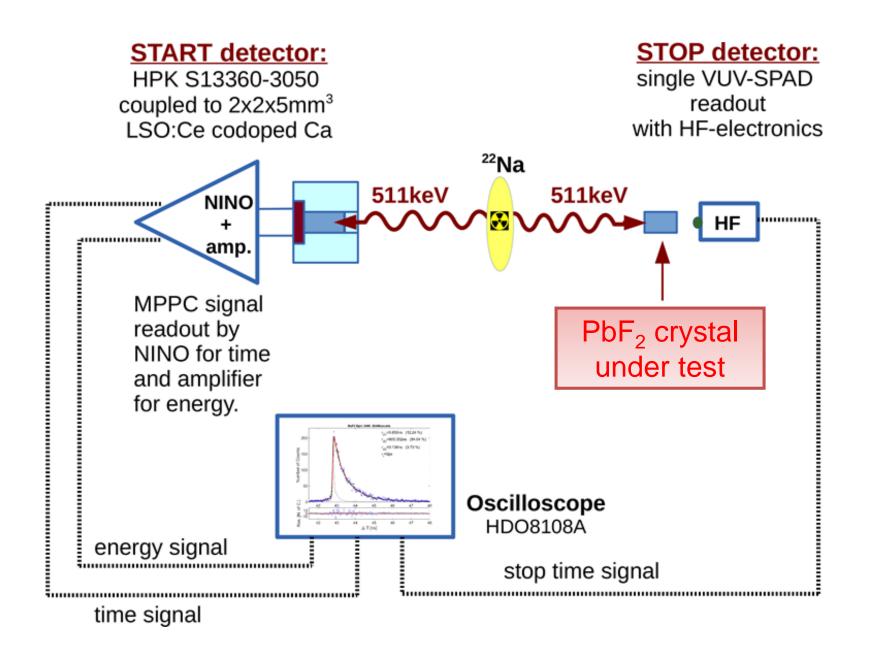




Timing performance

Optimization of SPTR with masking: CHK-HD

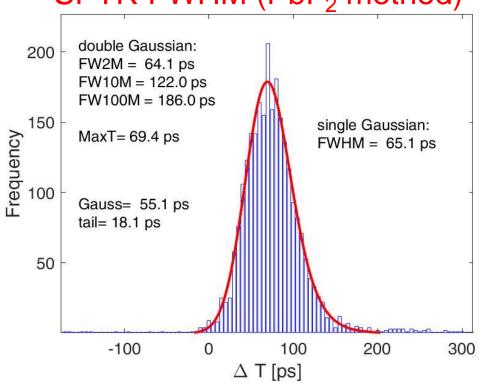
Using CHK-HD and high-frequency readout, S. Gundacker was able to measure excellent Single Photon Time Resolution, with a 3x3 mm² SiPM.





Intrinsic SPTR

SPTR FWHM (PbF₂ method)



$$SPTR_{intrinsic} = \sqrt{65^2 - 47^2 - 21^2} = 39.6 \ ps$$

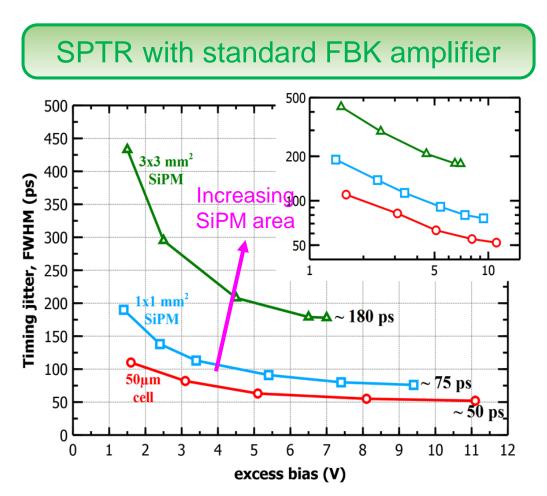


Nicolaus Kratochwil et al 2021 Phys. Med. Biol. 66 195001

Timing performance Effect of SiPM area on SPTR

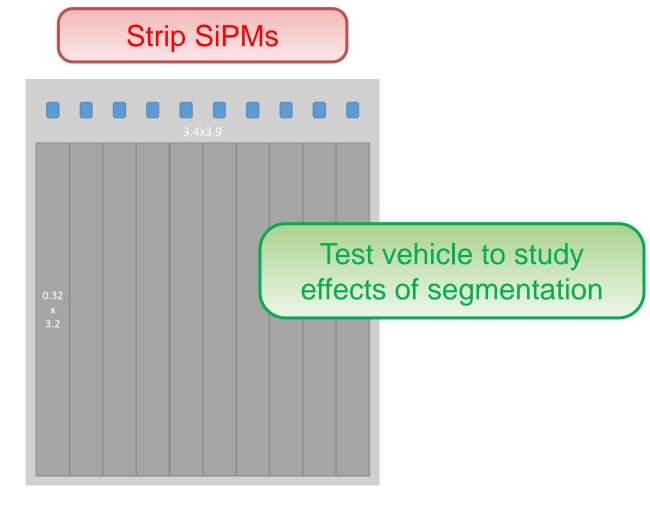
SPTR and CRT performance is degraded when reading out SiPMs with large areas.

A possible solution can be the *segmentation of the active area into small pixels*, with separate readout, followed by signal summation or combination of time pick-off information.



SPTR vs. excess bias for different SiPM sizes, *with traditional amplifier*.

10 strips 0.32 x 3.2 mm² each, no dead border between strips



Example of segmented SiPM layout: a 3x3 mm2 active area is divided in 10 0.3x3 mm2 strip-SiPMs.

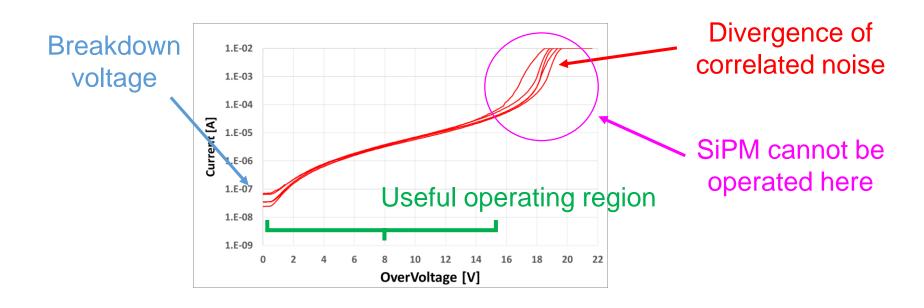


Acerbi, Fabio, et al. "Characterization of single-photon time resolution: from single SPAD to silicon photomultiplier." *IEEE Transactions on Nuclear Science* 61.5 (2014): 2678-2686.

Optical Crosstalk Worsening of the performance of the detection system

Optical Crosstalk worsens the performance of the detection system both by *limiting the maximum excess bias* that can be applied to the SiPM and by *worsening the photon time of arrival statistics*.

Limiting the maximum excess bias



Above a certain over-voltage the number of dark counts and, thus, the reverse current diverge.

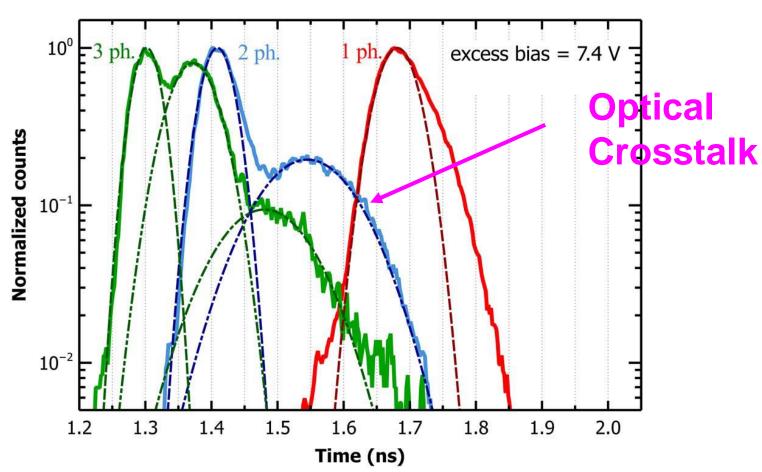
- Lower PDE, Gain.
- Worse SPTR

$$ECF \cong \frac{1}{1 - P_{CN}}$$

=5<

Geometric series approximation of the *Excess Charge Factor*.

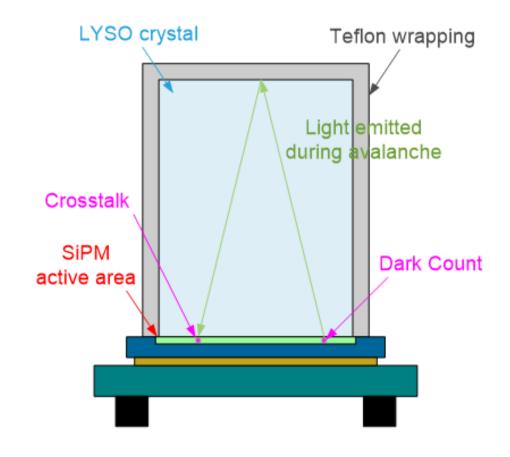
Worsening of the Few Photons Time Resolution



Few-photon time resolution measured with Leading-edge discriminator Additional peaks are most likely generated by (delayed) correlated noise.

Optical crosstalk External Crosstalk

Optical crosstalk probability is enhanced by the presence of the scintillator. external crosstalk.

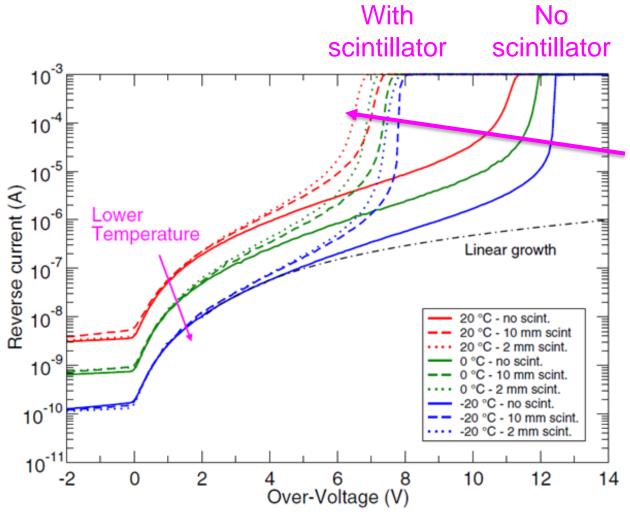


$$ECF \cong \frac{1}{1 - P_{CN}}$$

Geometric series approximation of the *Excess Charge Factor*.

Mechanism of optical crosstalk probability enhancement because of the scintillator.

Gola, Alberto, et al. "SiPM optical crosstalk amplification due to scintillator crystal: effects on timing performance." *Physics in Medicine & Biology* 59.13 (2014): 3615.



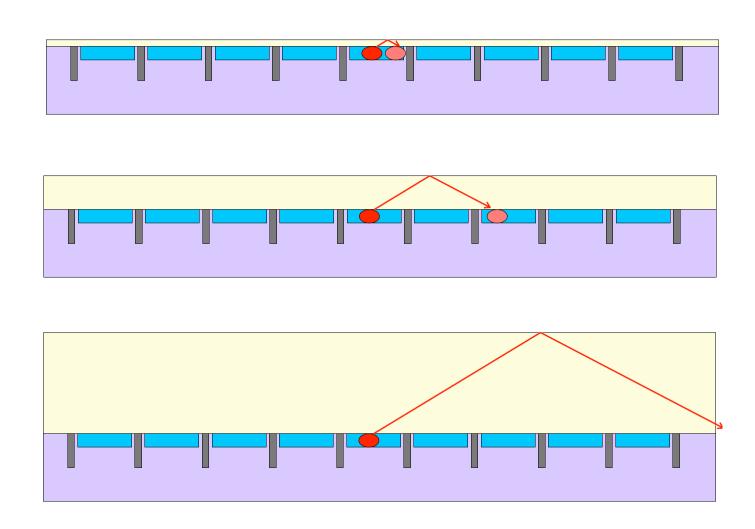
Comparison of SiPM IV with different scintillator sizes placed on top of them, at different temperatures.

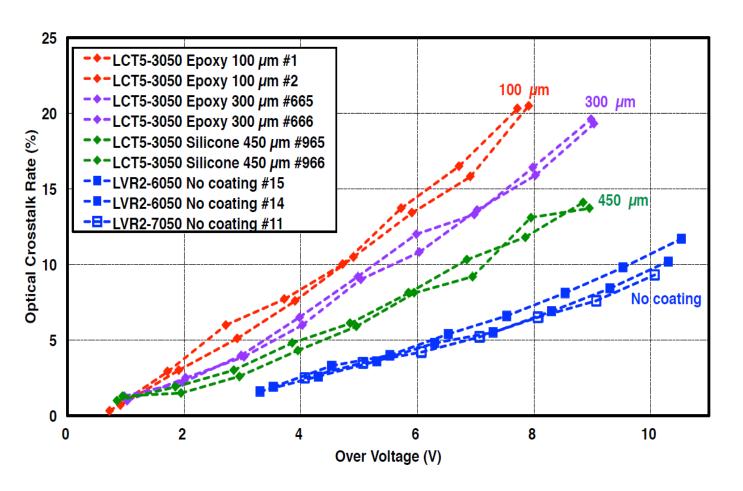


Optical crosstalk External Crosstalk and protective resin

The package geometry, in particular the resin thickness, has a significant effect on the optical crosstalk probability.

The effect was studied on Hamamatsu SiPMs and discussed in the ICASiPM conference.





We can identify an *optimal thickness of the encapsulating resin*

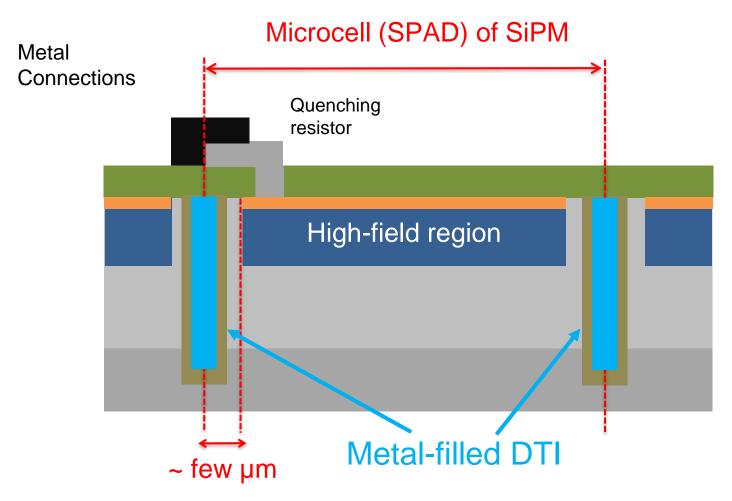


Reduction of optical crosstalk NUV-HD-MT development

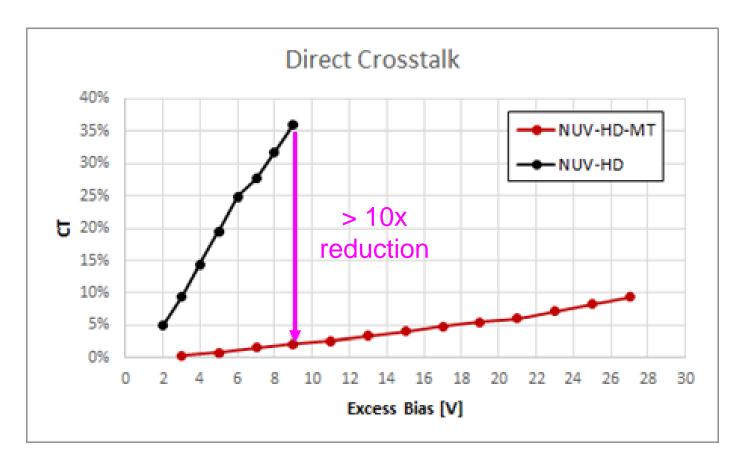


Starting from the NUV-HD technology, FBK and Broadcom jointly developed the NUV-HD-MT technology, adding *metal-filled DTI isolation to strongly suppress optical crosstalk*.

Other changes: low electric field variant, layout optimized for timing.



Conceptual drawing of the NUV-HD-MT, with the addition of metal-filled Deep Trench Isolation.



Reduction of optical crosstalk probability in NUV-HD-MT, compared to the "standard" NUV-HD. Measurement without encapsulation resin, i.e. *only considering internal crosstalk probability*.

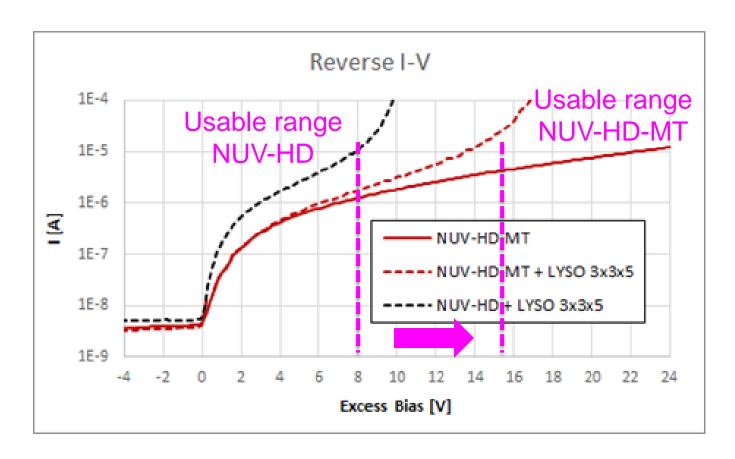


Reduction of optical crosstalk **NUV-HD-MT** bias range

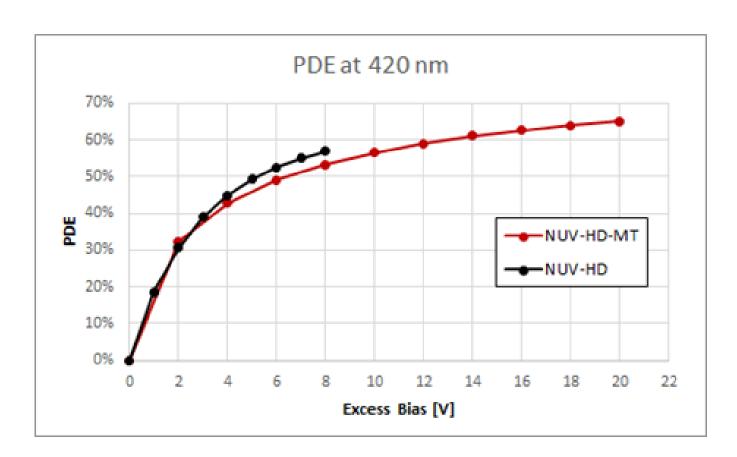


Reduction of optical crosstalk probability *increases maximum usable excess bias of SiPM*, also with the scintillator on top of the SiPM.

Increase of excess bias *more than compensates the slight reduction of Fill Factor* caused by the addition of metal inside the DTI.



Reverse IV measured on a 4x4 mm² NUV-HD-MT SiPM with 45 um cell pitch under different conditions.



PDE at 420 nm measured on a NUV-HD-MT SiPM with 45 um cell size.

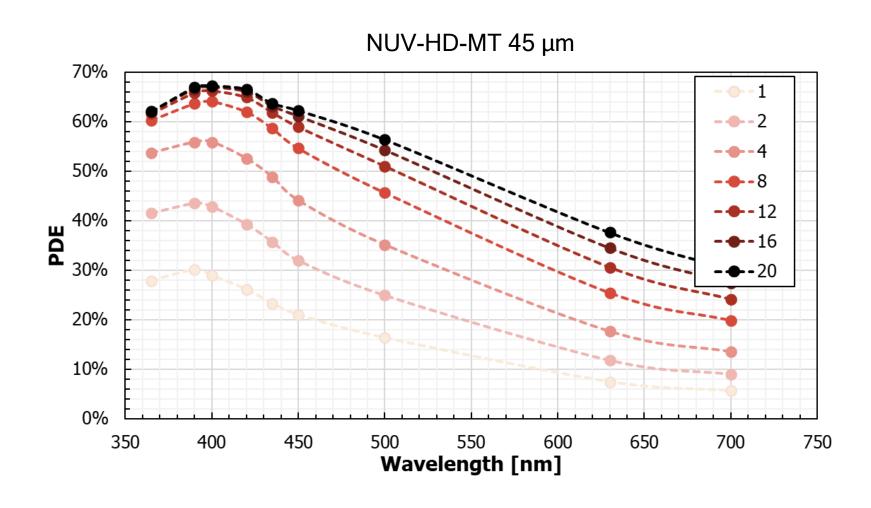


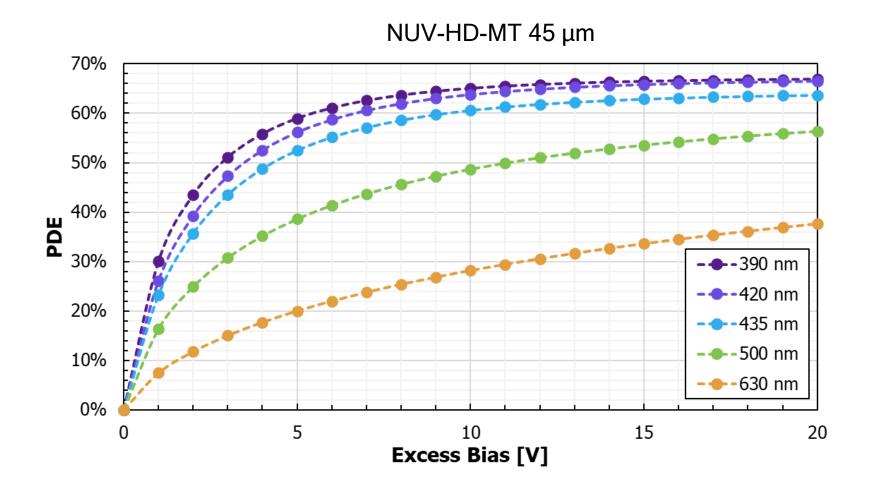
Reduction of optical crosstalk NUV-HD-MT PDE



NUV-HD-MT is *based on a p-on-n junction*, thus peak PDE is around 390 – 420 nm.

Thanks to the very high maximum excess bias, also PDE in the red (avalanche triggering by holes) approaches saturation.



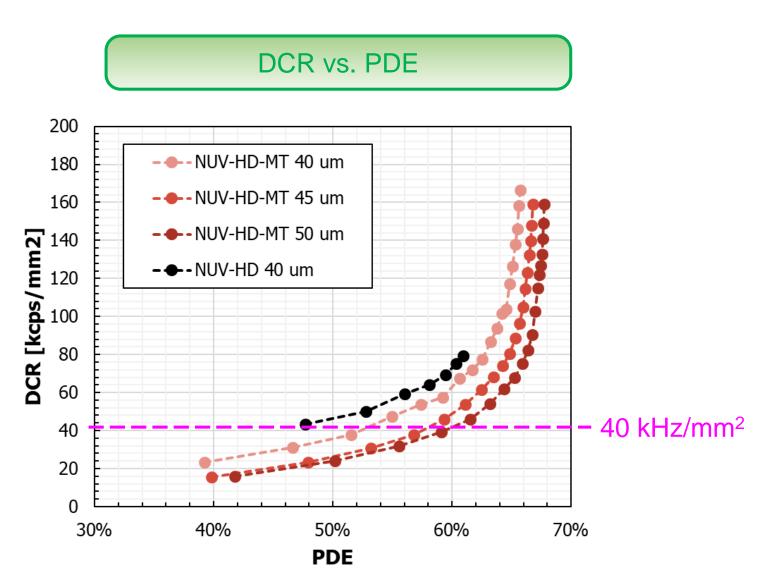




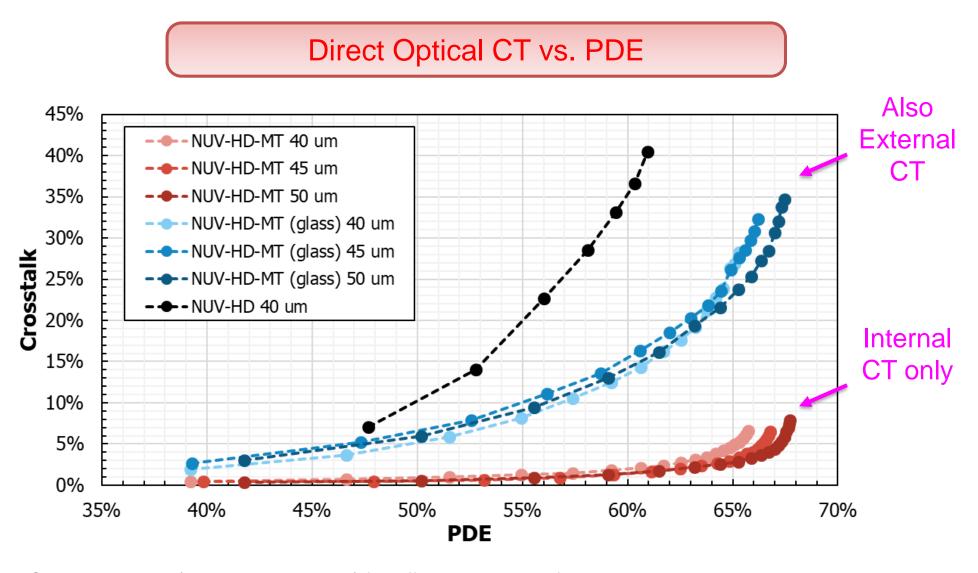
Reduction of optical crosstalk NUV-HD-MT electro optical performance



NUV-HD-MT nuisance parameters are better represented and compared as a function of the PDE.



DCR vs. peak PDE (measured at 420 nm) for different cell sizes of the NUV-HD-MT technology.



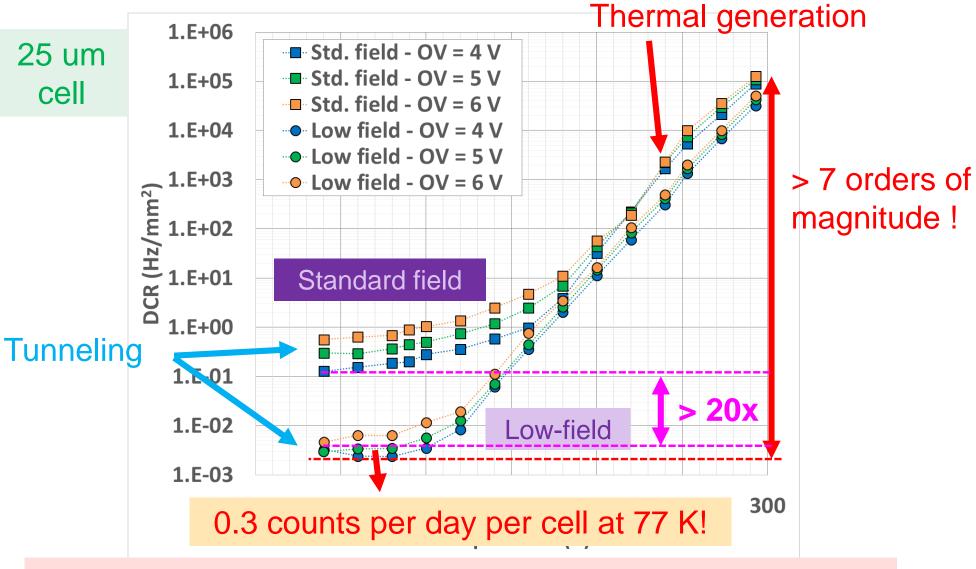
DiCT vs. peak PDE (measured at 420 nm) for different cell sizes of the NUV-HD-MT technology, with and without protective glass on top of the SiPM (used for TSV)

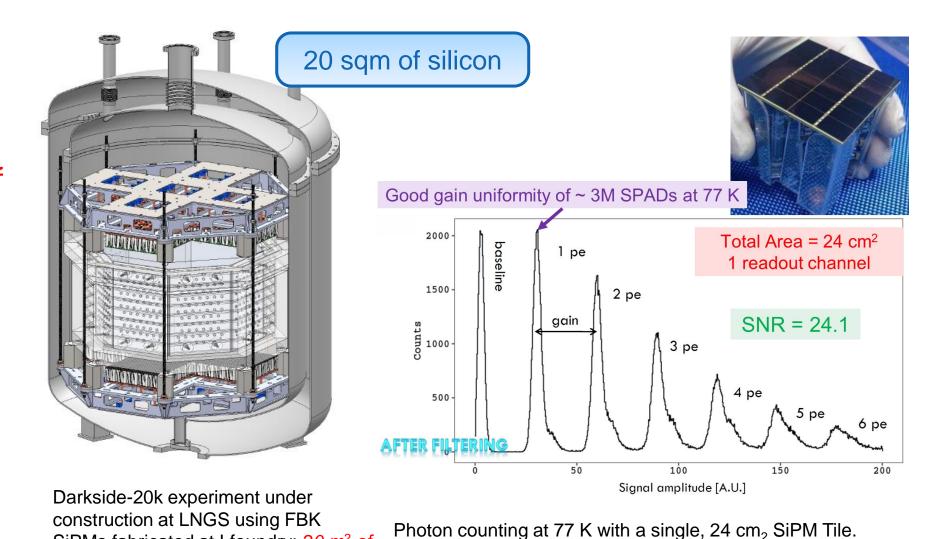


Cryogenic operation DarkSide-20k SiPMs



NUV-HD-Cryo SiPM technology is an *enabling technology for the DarkSide-20k* experiment, currently under construction.





A 10x10 cm² SiPM array would have a total DCR < 100 cps!

Reduction of Dark Count Rate at cryogenic temperature thanks to electric field engineering in FBK SiPMs.



Acerbi, Fabio, et al. "Cryogenic characterization of FBK HD near-UV sensitive SiPMs." *IEEE Transactions on Electron Devices* 64.2 (2017): 521-526.

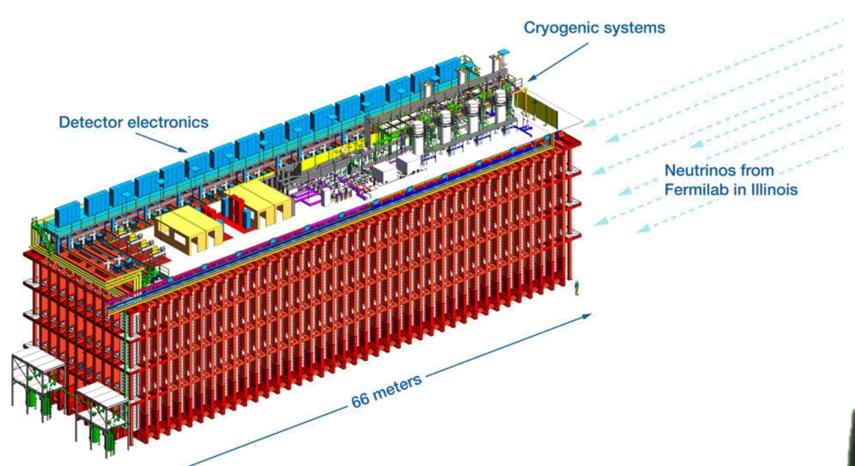
SiPMs fabricated at Lfoundry: 20 m² of

SiPMs operated at 87 K.

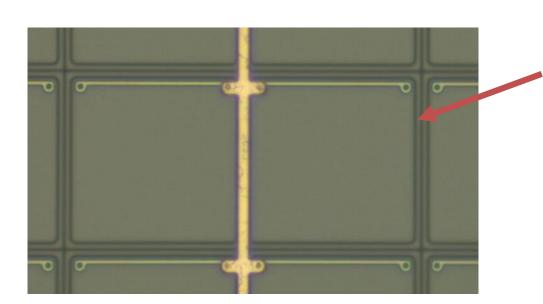
Cryogenic operation DUNE SiPMs



NUV-HD-Cryo SiPM technology is at the basis of the *ongoing R&D collaboration between FBK and UniMiB* for the production of >250k channels for the DUNE experiment.



One of the four far-detector modules for the Deep Underground Neutrino Experiment.



SiPM microcell optimized for DUNE



Prototype 6-channel array based on NUV-HD-Cryo fabricated at Lfoundry and packaging developed by FBK.



Triple trench

isolation

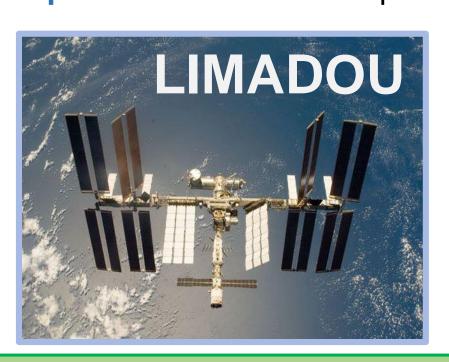
Radiation Hardness Motivation for R&D

Improving radiation hardness of SiPMs is one of the next frontiers of development at FBK for very important applications, both in big science experiments and in space.

Detectors for collider experiments: from 10¹⁰ neq/cm² to >10¹⁴ neq/cm²



Geostationary orbit space experiments: ~5·10¹¹ neq/cm²



What is the definition of radiation hardness for SiPMs?

R&D approach:

- Qualification of radiation tolerance of current SiPM technologies.
- Study / modeling of the effects of radiation damage on SiPM characteristics, under different sources of radiation.
- Development of a *highly customized SiPM technology* for optimal performance after irradiation is likely needed.



Test Beam 1 – Trento Proton Therapy Experimental Setup and DoE

Relatively low maximum irradiation dose, targeting space applications and certain HEP experiments.

Energy. 148 MeV source + inhibitor → *74 MeV proton energy*

```
Dose: 12 dose steps:

^{\sim} 5.10^6 - 4.10^{11} \text{ p/cm}^2

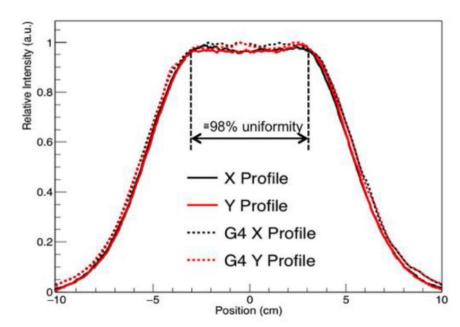
↓ (NIEL scaling hypothesis)

^{\sim} 7.10^6 - 6.10^{11} 1 \text{ MeV } n_{ed}/\text{cm}^2
```

Analysis:

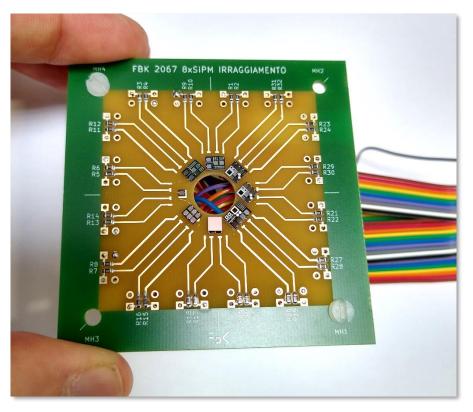
- Online IV measurement between each irradiation step;
- Functional measurements after 1 month RT annealing:
 - → Waveform analysis on irradiated samples only at -40°C (High DCR, event separation is not possible / reliable above 20 Mc.p.s.)





Tommasino (2019) https://doi.org/10.1016/j.ejmp.2019.02.001

"Dual ring setup"[1]: 98% uniformity on ~6 cm diameter

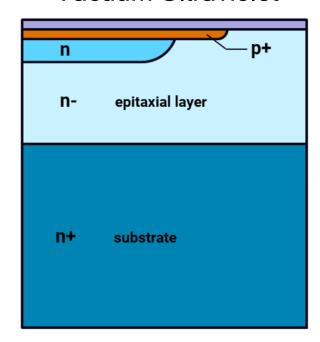


Customized PCB for irradiation tests, housing multiple SiPMs and allowing online IV measurements.

Test Beam 1 – Trento Proton Therapy Tested Technologies

We tested a relatively wide range of different customized SiPM technologies, fabricated in FBK internal R&D clean-room, looking for differences, general trends, etc..

VUV-HD^[2] Vacuum Ultraviolet



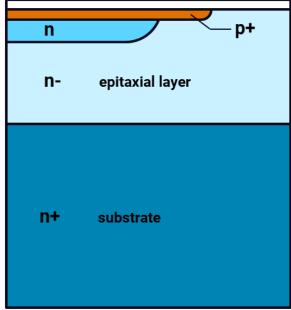
Peak PDE = 420 nm

- Different ARC
- High sensitivity in VUV

[2] Capasso (2020) https://doi.org/10.1016/j.nima.2020.164478

NUV-HD^[3]

Near Ultraviolet



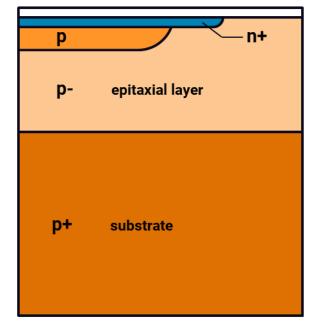
Peak PDE = 420 nm

- CRYO = Cryo temp opt.
- RH = High radiation opt.

[3] Gola (2019) https://doi.org/10.3390/s19020308

RGB-HD^[4]

Visible

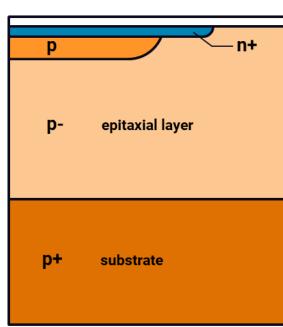


Peak PDE = 530 nm

[4] Ferri (2015) https://doi.org/10.1186/2197-7364-2-S1-A86

NIR-HD^[5]

Near Infrared



Peak PDE = 530 nm

- Thick epitaxial layer
- High sensitivity in IR

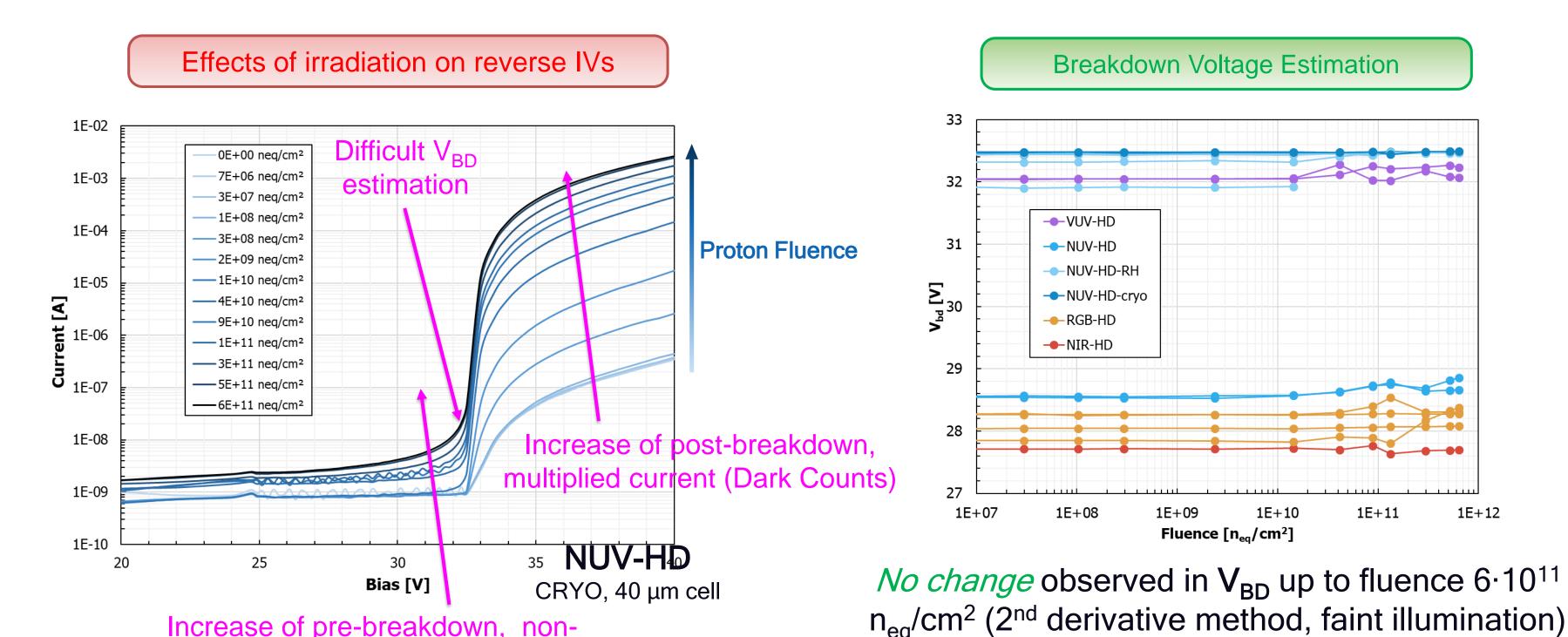
[5] Acerbi (2018) https://doi.org/10.1016/j.nima.2017.11.098



Test Beam 1 – Trento Proton Therapy **Online IV measurements**

Increase of pre-breakdown, non-

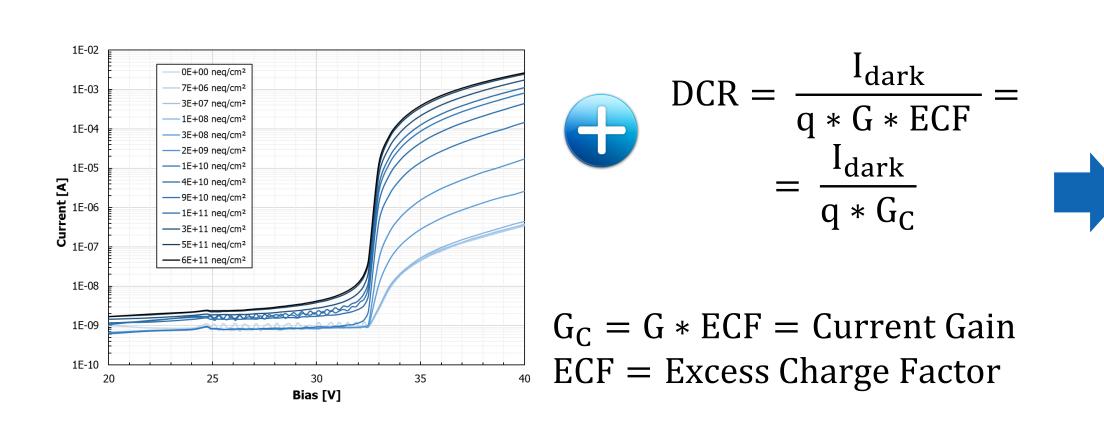
multiplied (~surface) current



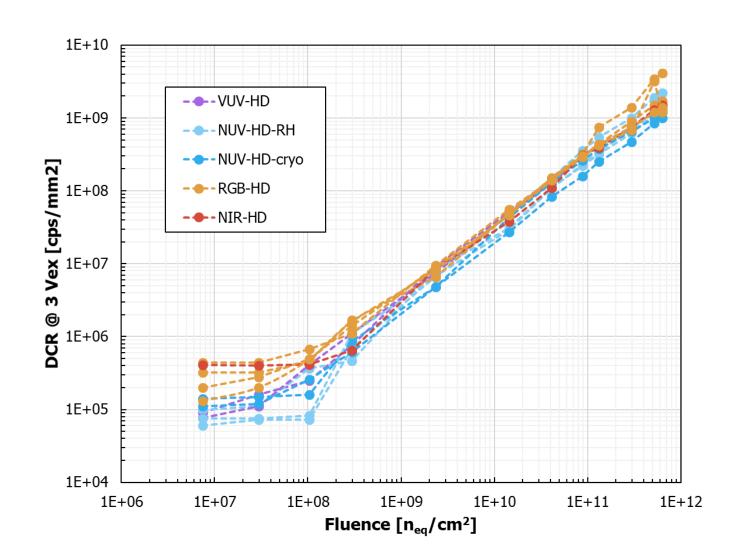


Test Beam 1 – Trento Proton Therapy Dark Count Rate Estimation from reverse IV

Comparison of radiation hardness of different SiPM technologies cannot be done directly from their IVs because they usually have different Gain and correlated noise (ECF).



Assumption: ECF and Gain do not change with irradiation (will be shown later)



DCR estimation for different FBK SiPM technologies.



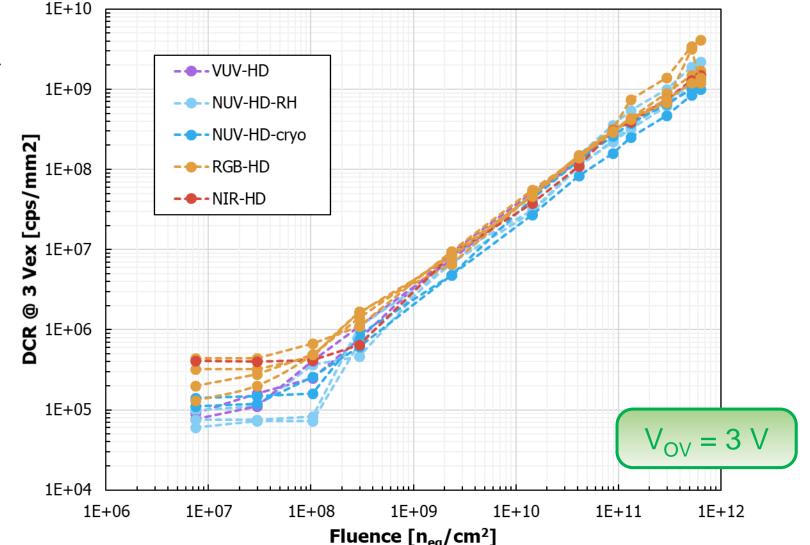
Test Beam 1 – Trento Proton Thera Dark Count Rate vs. Fluence

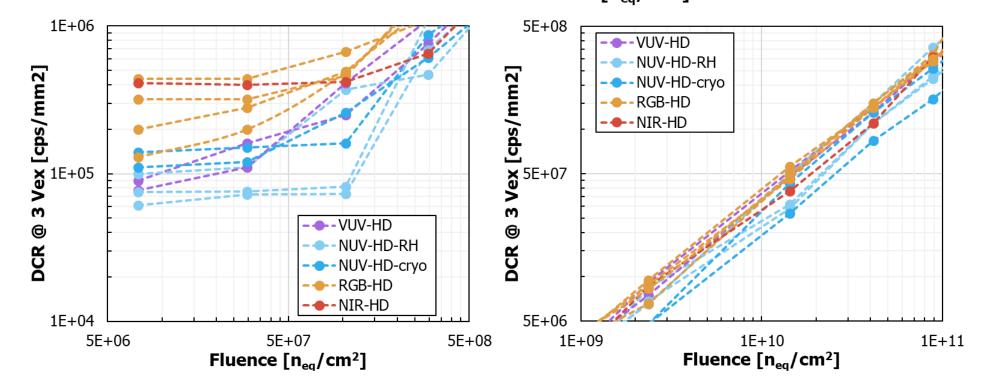
There is *little correlation between the DCR before and after irradiation*:

- All technologies seem to "converge" towards similar values
- Knee between $10^7 \div 10^8 \text{ n}_{eq}/\text{cm}^2$
- Independence of bulk damage from contaminants in the SiPM starting material?



- from \sim 1 OoM to $< \sim$ 0.5 OoM
- Still worth investigating differences between technologies







Test Beam 1 – Trento Proton Therapy Damage Factor

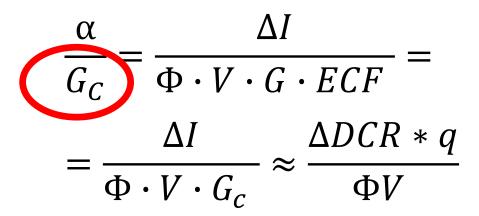
To estimate the sensitivity of different SiPM technologies to the radiation damage, we suggest using a version of the Damage Factor, modified for the Geiger-mode detectors.

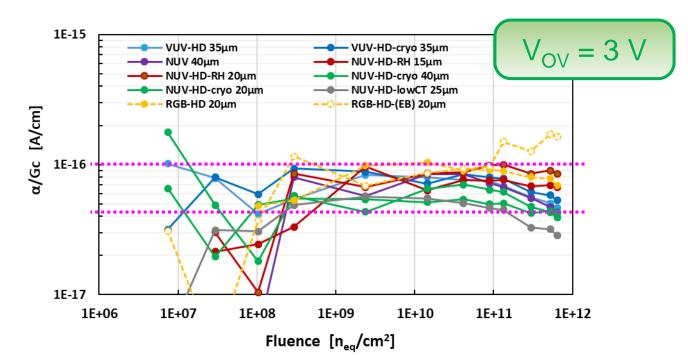
<u>Damage Factor</u> detectors without internal gain

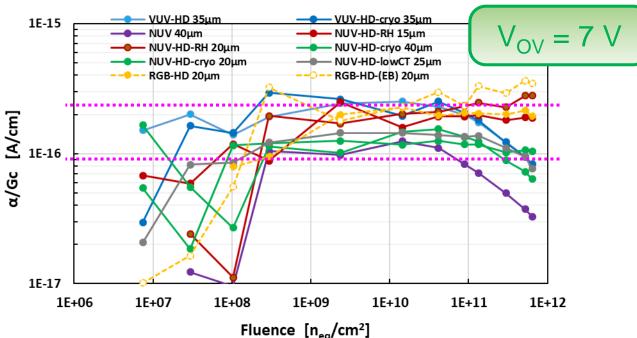
$$\alpha = \frac{\Delta I}{\Phi V}$$



<u>Damage Factor</u> Geiger-mode detectors







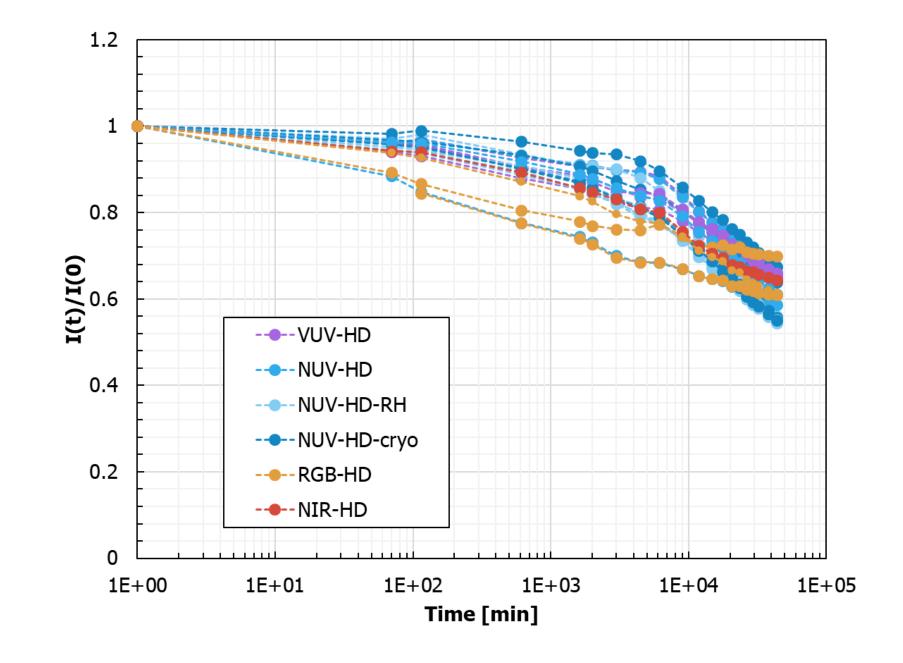
- Constant wrt. Irradiation dose.
- In accordance with literature
- Uniform behavior across different technologies: 5-10·10⁻¹⁷ A/cm²
- Dependence on excess bias: triggering probability and field-enhanced generation
- Which volume should be considered? (high E-field or collection region)



Test Beam 1 – Trento Proton Therapy First Annealing studies

Annealing can be a powerful mean of reducing DCR after irradiation to recovers single-photon resolution.

- Room temperature annealing (20-25°C) on the highest dose only (6.4·10¹¹ 1 MeV n_{eq}/cm²)
- Two slopes observed: knee point at around 1.5-10³ min (~1 day)
- Minor dependence on excess bias for a few samples.
- Higher annealing temperatures have demonstrated better annealing:
 - Factor > 10 after $1 \cdot 10^{11} n_{eq}/cm^2$ is reported in M. Calvi - https://doi.org/10.1016/j.nima.2019.01.013
 - *Is there a threshold temperature* for the annealing of certain defects?

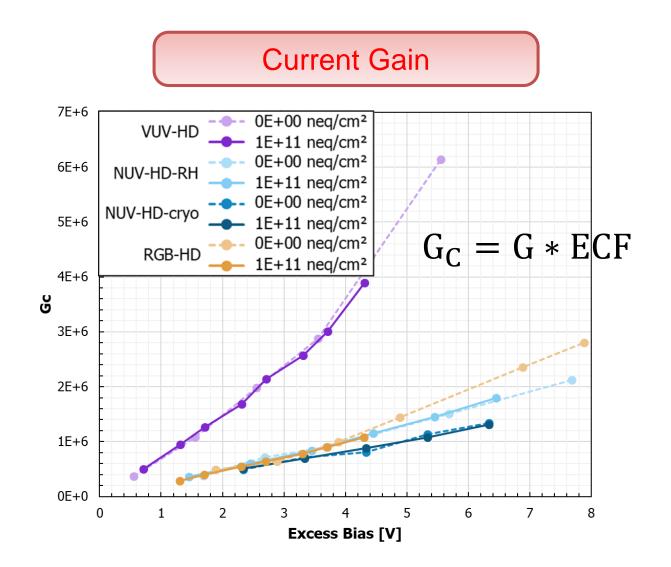




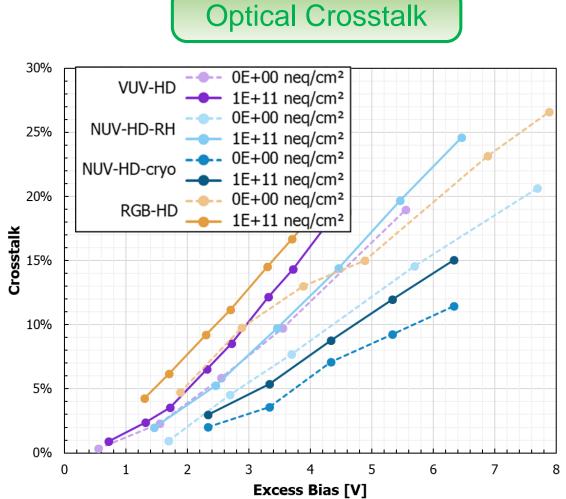
Test Beam 1 – Trento Proton Therapy Variation of the other SiPM parameters

Waveform analysis carried out at -40°C to reduce pile-up on the highest irradiation dose (1·10¹¹ n_{ea}/cm²).

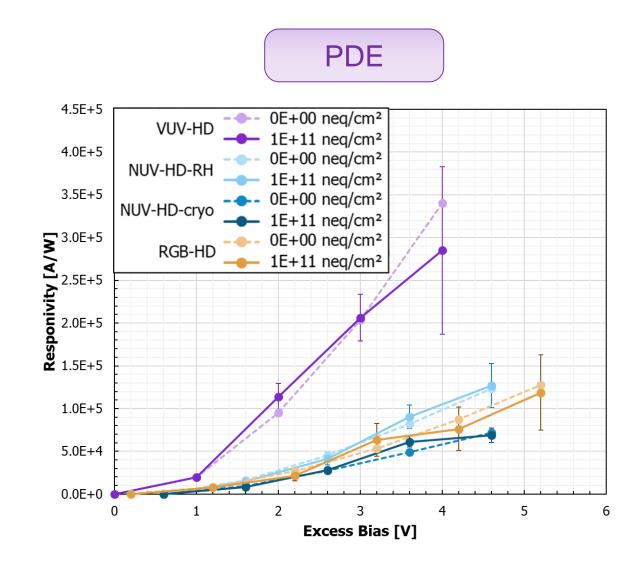
No relevant change of the other SiPM parameters, except for the DCR.



No change in Gain * ECF up to 1·10¹¹ n_{eq}/cm²



Minor increase of CT is most likely an artifact caused by pile-up.



No change in PDE, measured as responsivity (loss of single photon resolution).



Test Beam 2 – LNS Catania Experimental Setup and DoE

A test beam was carried out at LNS in Catania in 2019, focusing on higher irradiation doses and

temperature dependence studies.

Energy: 62 MeV protons

Dose: 5 samples irradiated with different doses:

 $\sim 7.4 \cdot 10^9 - 6.5 \cdot 10^{13} \text{ p/cm}^2$

 $\sim 1.3 \cdot 10^{10} - 1.1 \cdot 10^{14} 1 \text{ MeV n}_{eq}/\text{cm}^2$

Analysis: after irradiation, on each sample:

Devices: NUV-HD-RH

15 um cell size

1x1 mm² active area



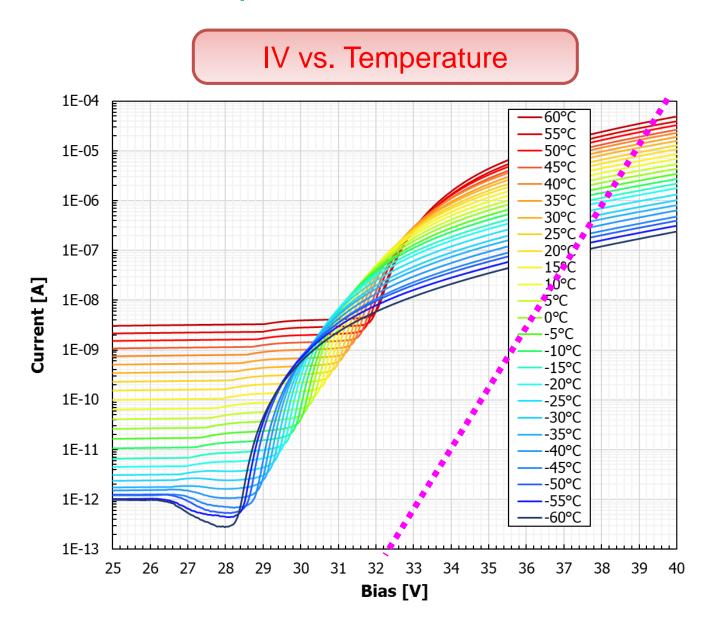


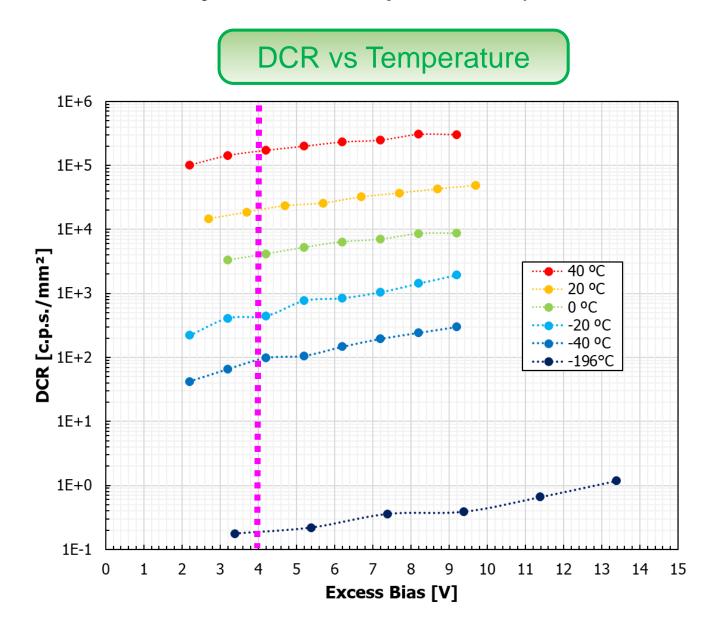
Test Beam 2 – LNS Catania DCR Analysis



Study of DCR after irradiation extended to cryogenic temperatures (preliminary).

- *IV vs Temperature*: +60°C → -60°C
- *DCR vs Temperature*: +40°C → -40°C, LN₂ (waveform analysis, when possible)

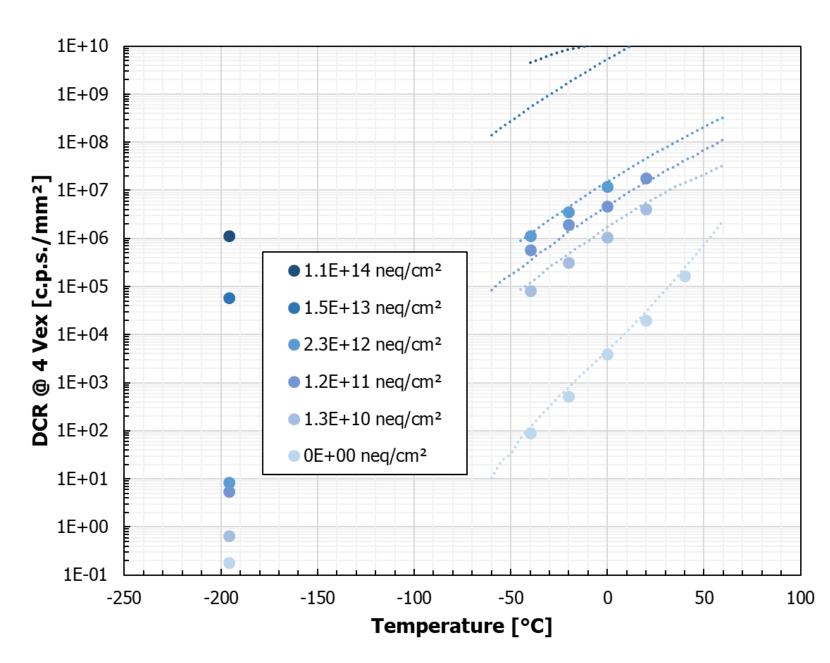






Test Beam 2 – LNS Catania DCR vs. Temperature and Dose





Lines: DCR from IV

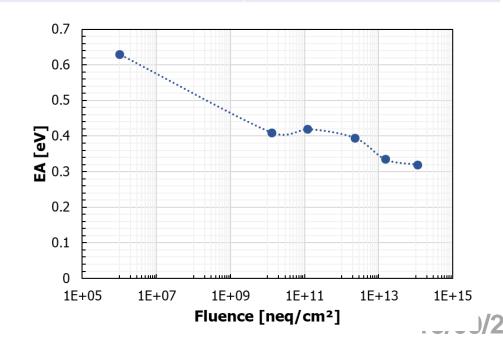
Dots: DCR from waveform analysis



→ Cooling becomes less effective in reducing DCR.



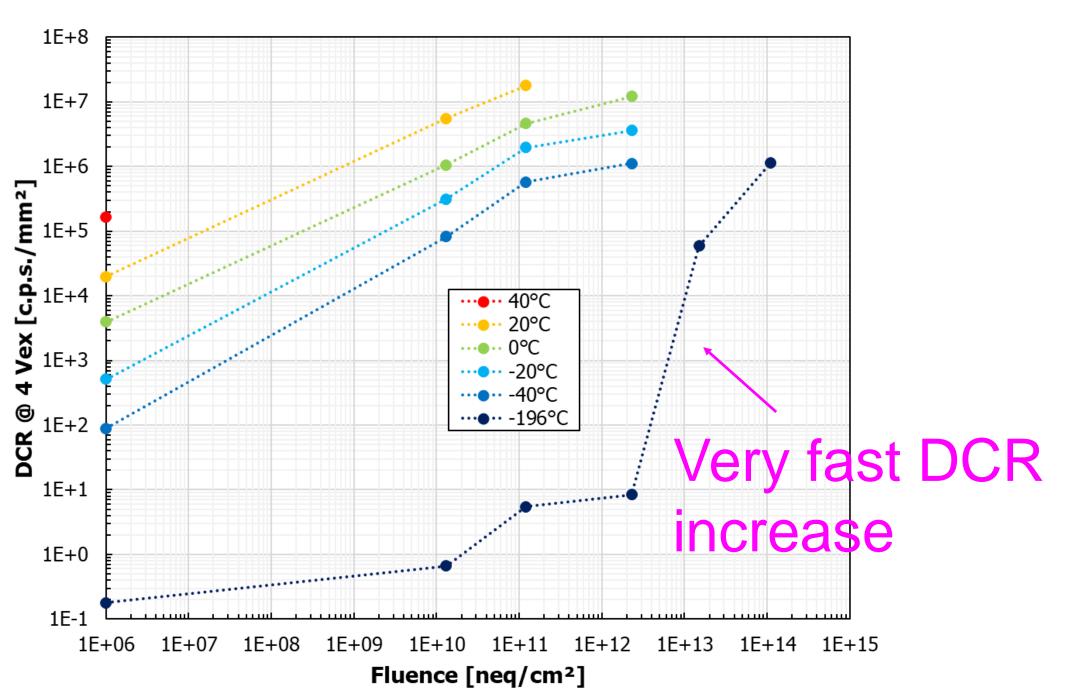
Fluence [n _{eq} /cm ²]	E _A [eV]
0E+00	0.63
1.3E+10	0.41
1.2E+11	0.42
2.3E+12	0.40
1.5E+13	0.34
1.1E+14	0.32





Test Beam 2 – LNS Catania DCR at LN after irradiation





- Cooling is extremely effective in reducing DCR after irradiation up to ~1·10¹² n_{eq}/cm²
- Further investigations needed to understand what happens at the higher doses
- Worth checking different / new SiPM structures
- Check possible effect of annealing



Radiation Hardness Definition + Mitigation strategies

It is rather obvious that we cannot prevent the bulk damage from increasing the DCR of the SIPM.

A possible definition of Rad-Hardened / tolerant SiPM is a SiPM that retains its target performance in a given application even after radiation damage.

- → Depends on the application!
- → Radiation damage mitigation strategies (+ annealing)

Use of small cells + Engineering of electric field

Issue / Hypothesis	Technical Solution	Mitigation
Increase of primary DCR	Electric field engineering	Better DCR temperature coefficient High PDE at lower bias (to reduce field-enhanced effects)
PDE loss due to cells busy triggering dark counts.	Smaller Cells	More cells and faster recharge: lower PDE loss.
Increased power consumption due to higher DCR.	Smaller Cells	Lower gain: less current (for a given DCR).

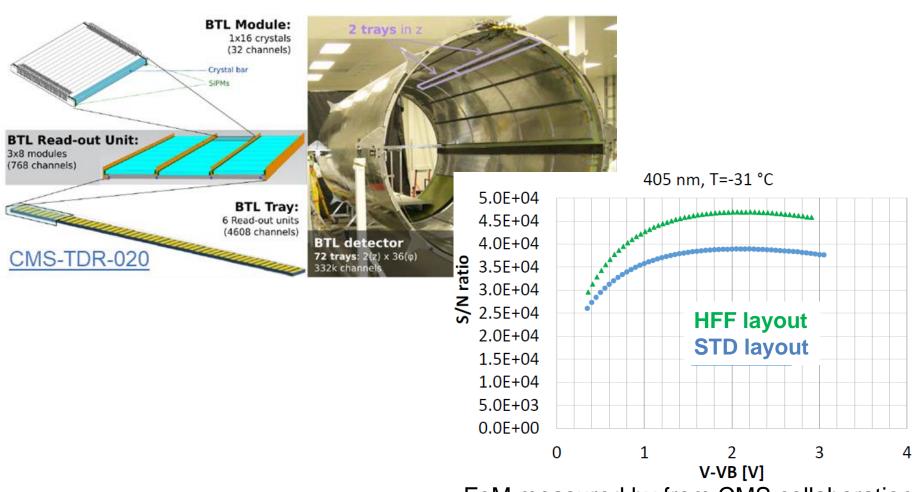


Mitigation of Radiation Damage NUV-HD-RH SiPMs for CMS-BTL

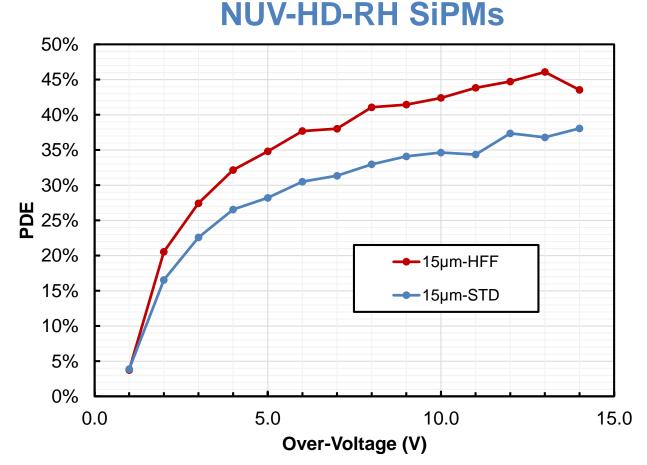


SiPMs with extreme radiation tolerance are required for the Barrel Timing Layer of the CMS experiment, at CERN: 1.9×10¹⁴ 1 MeV n_{eq}/cm².

Custom SiPM technology was developed, combining *electric field engineering with small-pitch SiPM technology*, for enhanced radiation hardness.



FoM measured by from CMS collaboration: A. Heering, Y. Musienko, M. Lucchini et al.)



The advantage of using small cells for radiation hardness is relevant *only if* they can still provide very high PDE

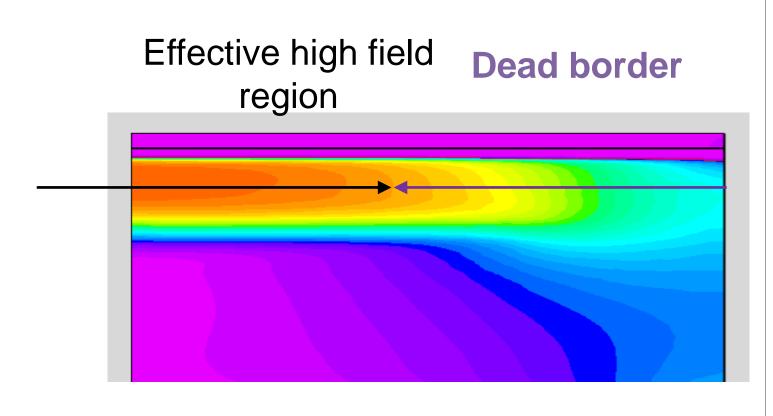


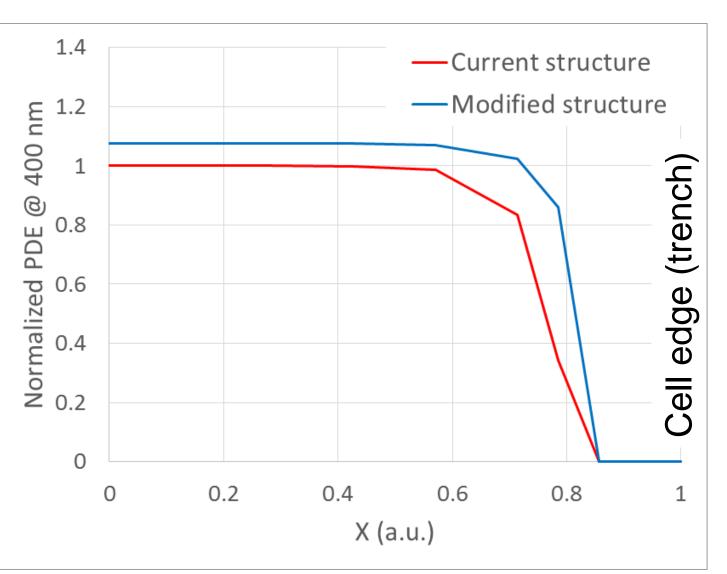
Mitigation of Radiation Damage NUV-HD-RH SiPMs for CMS-BTL



R&D still in progress to improve the electric field profile and to select optimal cell size:

- Narrower dead border at small OV
- Faster increase of PDE vs OV





Simulated PDE @ 400 nm vs normalized distance from cell center

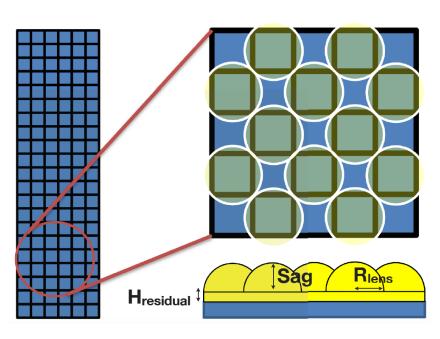


Light concentration Microlenses

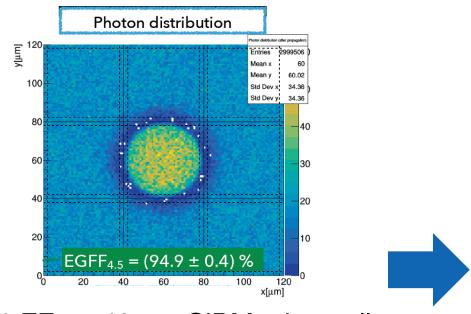


Microlenses can be used to enhance the Fill Factor (FF) and thus the PDE of the SiPM microcells.

- Exploratory project between FBK and EPFL for LHCb SciFi tracker → Sensitivity-enhanced SiPMs
- Effectiveness depends on the angular distribution of photons.



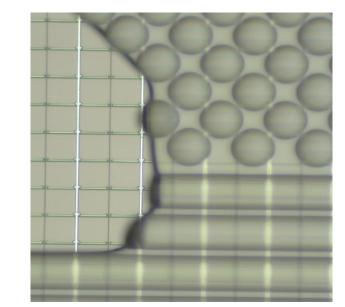
Proposed microlens geometry



95% FF on 40 um SiPM microcells (80% without microlenses)

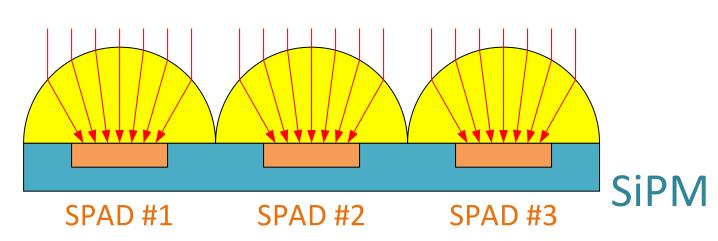
Microlenses to enhance radiation hardness

- Photons can be focused on a much smaller light-sensitive area within each microcell.
- The silicon area sensitive to radiation damage is reduced.



23% improvement!

Courtesy of C. Trippl, G. Haefeli https://doi.org/10.1016/j.nima.2022.167216





Light concentration **Metasurfaces and Metamaterials**



nanophotonics.



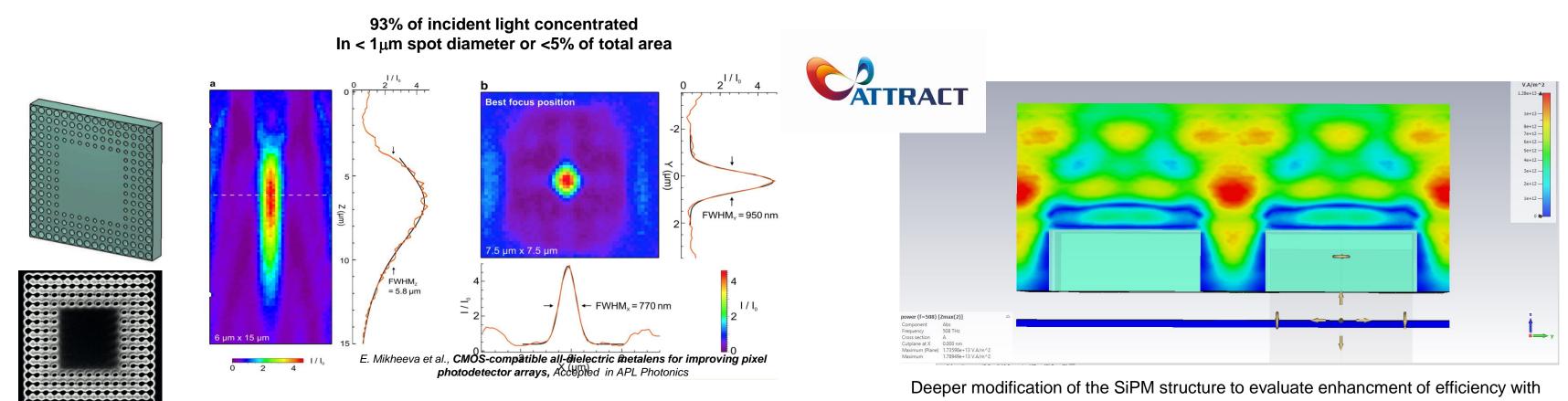




FBK investigated the possibility of *using nanophotonics to enhance SiPM performance* in the context of the PHOTOQUANT ATTRACT project.

Metalens-based light concentrators can work similarly to microlenses to enhance SiPM radiation hardness.

Advantages: rad-hard metalens material (TBC), compatibility with CMOS planar processing.



Experimental metalens designed and fabricated 4x4µm Nb₂O₅ metalens with refractive index gradient introduced by holes of varying diameter, (joint ATTRACT project CERN, FBK, Institut Fresnel.)



E. Mikheeva et al., CMOS-compatible all-dielectric metalens for improving pixel photodetector arrays, Accepted in APL Photonics

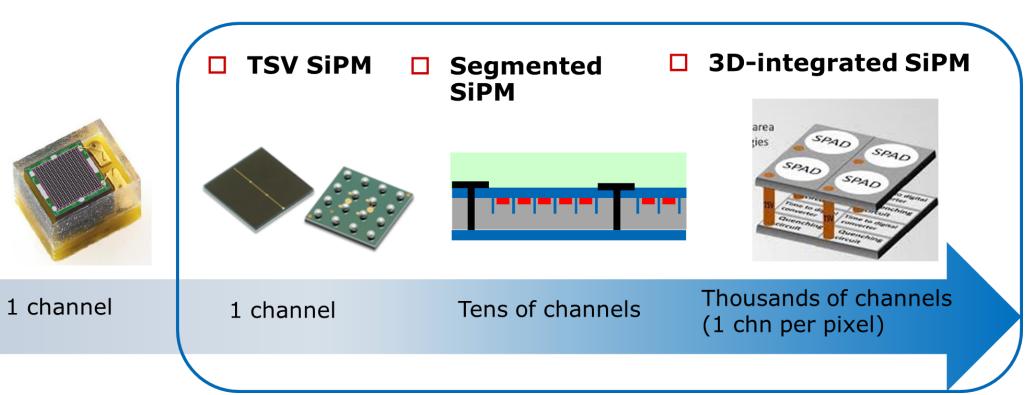
2.5D and 3D Integration FBK IPCEI clean-room upgrade

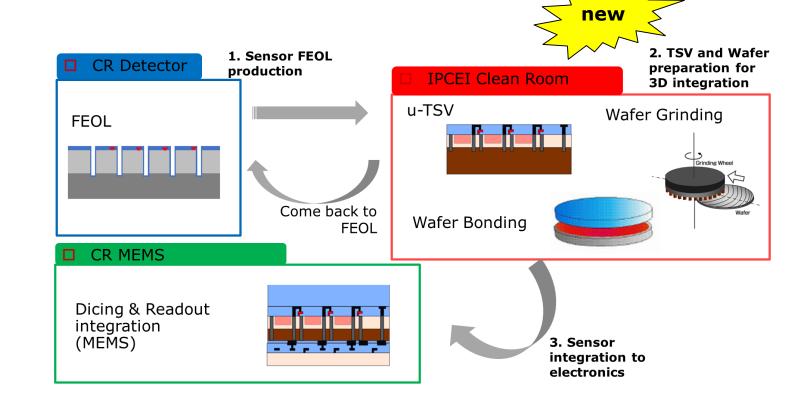


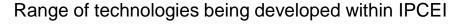
FBK is part of the *IPCEI on microelectronics* project (Important Project of Common European Interest - €1.75 billion total public support, 12 M€ to FBK).

The goal for FBK is upgrading its optical sensors technologies, by developing TSVs, micro-TSV and Backside Illuminated SiPMs. This will allow high-density interconnections to the front-end and high-segmentation.

Customized TSVs will be optimized to preserve the NUV-HD electro optical and timing performance.







The future system composed of 3 research clean-rooms in FBK.

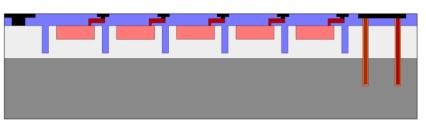
New clean-room under construction for 3D integration

2.5D and 3D Integration TSV – via mid: process flow

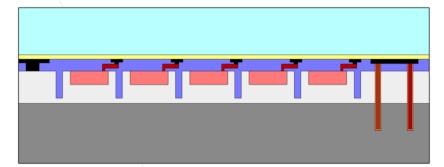


In the via-mid process, the TSV is formed during the fabrication of the SiPM, modifying its process flow.

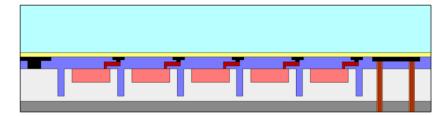
SiPM fabrication + TSV formation



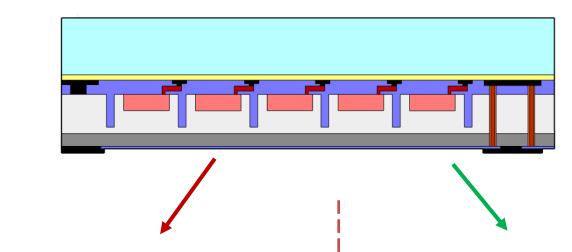
Edge Trimming + BONDING



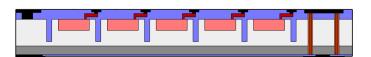
THINNING



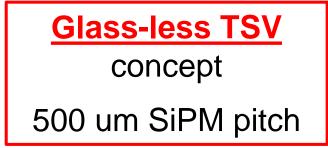
Contacts formation



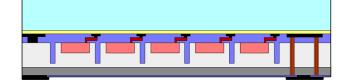
DEBONDING



Thickness at least 150 um



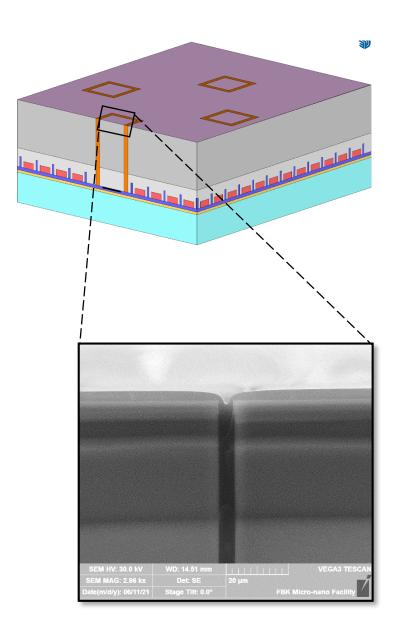
NO-DEBONDING



Thickness 10-50 um



< 50 um SPAD pitch

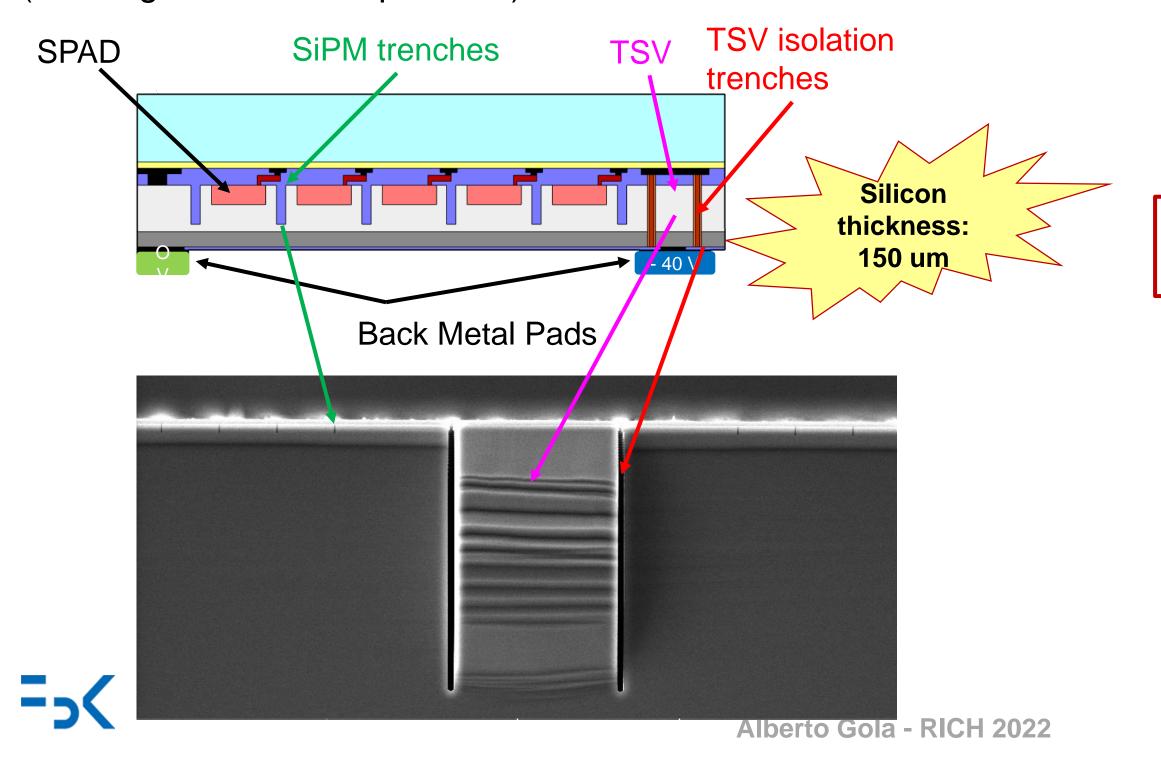




2.5D and 3D Integration TSV – via mid: first results



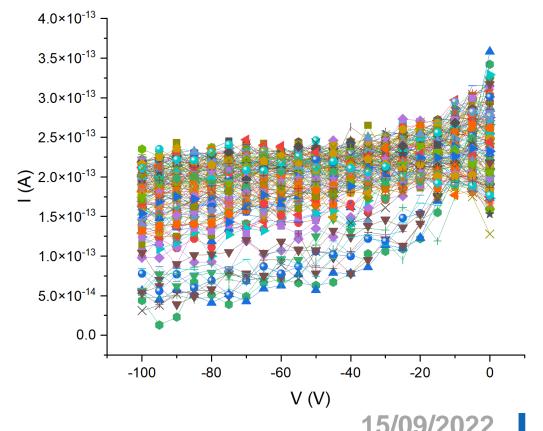
Preliminary results on TSV via-mid development, with partial SiPM process, to check isolation and continuity (no Geiger-mode multiplication).



At **-100 V** of bias applied the intensity varies from 30 to 200 fA



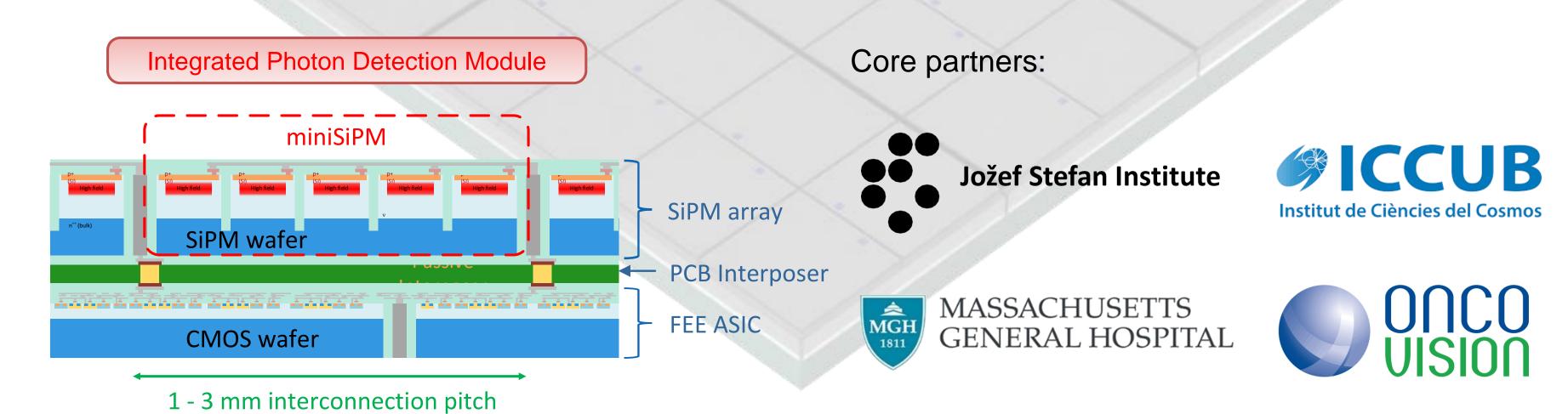
Trough Silicon Vias – Via Mid are isolated from the bulk silicon contact



2.5D and 3D Integration 2.5D integrated SiPM tile

In the *short and medium term*, medium density interconnection seems the sweet spot to obtain *excellent* performance (e.g. timing) on large photosensitive areas while not increasing complexity and cost too much.

We propose a Photon Detection Module (PDM) in which SiPMs with TSVs down to 1 mm pitch are connected to the readout ASIC on the opposite side of a passive interposer, in a 2.5D integration scheme.





Hybrid SiPM module being developed for ultimate timing performance in ToF-PET

2.5D and 3D Integration 2.5D integrated SiPM tile for timing



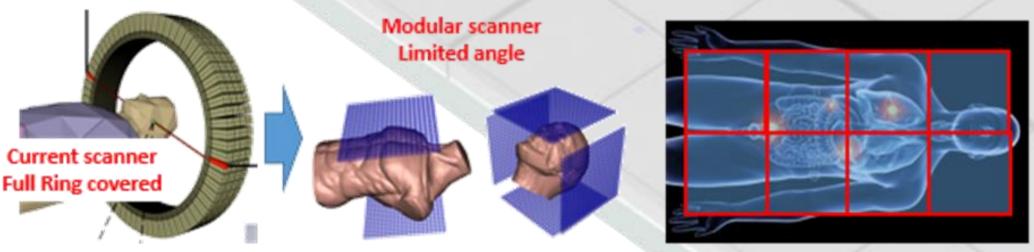




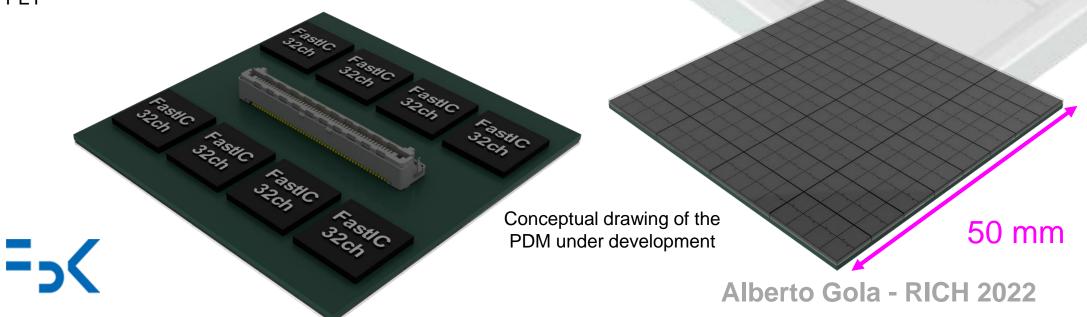


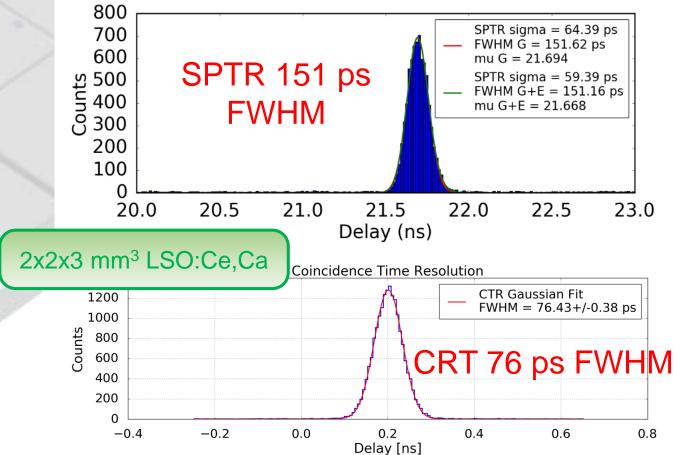
The 2.5D integrated PDM (50x50 mm²) will be the basis of a 30x30 cm² ToF-PET panel, which will be used to build limited-angle ToF-PET systems, for brain PET, Cardiac PET and full-body scanners.

We expect very good timing performance, supported by preliminary measurements achieved with NUV-HD SiPMs coupled to FastIC ASIC.



Application of the PDM to build large panes used in new, limted-angle PET applications: Brain Pet, Cardiac PET, while-body PET





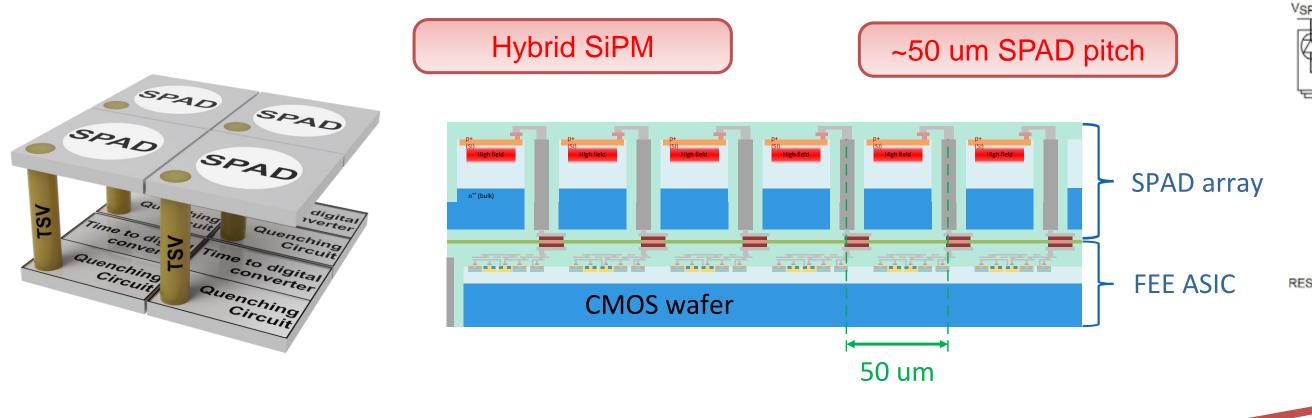
SPTR and CRT measured at FBK NUV-HD-SiPMs read by the FastIC ASIC developed by ICCUB.

Sensor: NUV-HD-LFv2 SiPMs, 3x3 mm² Scintillator: 2x2x3 mm³ LSO:Ce,Ca Power consumption: 3 mW / channel

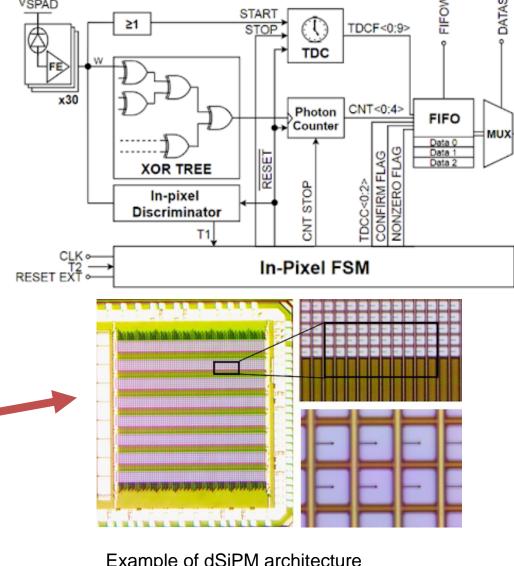
15/09/20

2.5D and 3D Integration Full 3D integration with micro TSVs: Hybrid SiPM

FBK is investigating the potential of microTSVs to achieve *single cell connection*. While complexity of the system increases, it might provide *ultimate timing performance*.



- FBK can apply all the know-how on system architecture already developed in the filed of digital SiPMs.
- Finally solve the duality between analog and digital SiPM: Hybrid SiPM concept.

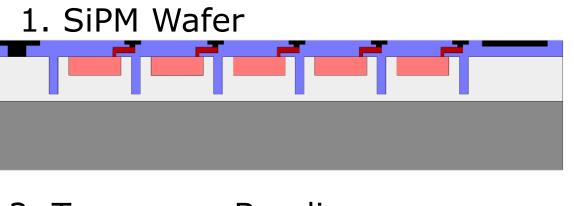


Example of dSiPM architecture developed at FBK (SBAM project)

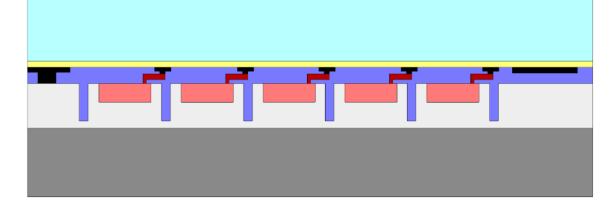
2.5D and 3D Integration **Backside Illuminated SiPMs: process flow**



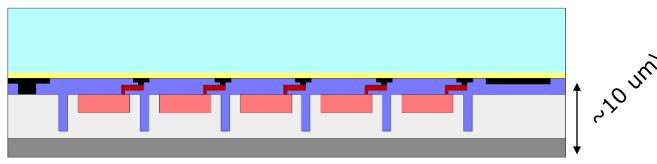
BSI development started on NIR-sensitive SiPMs -> no need to create a new entrance window on the backside with high efficiency in the NUV.



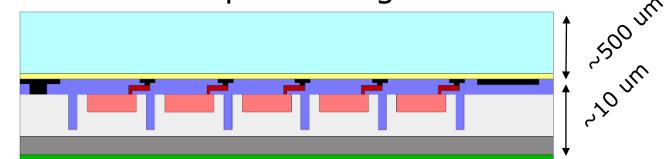




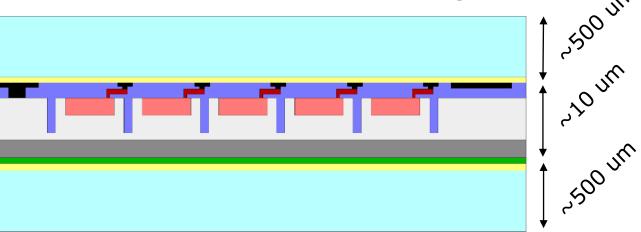
3. Grinding & Polishing



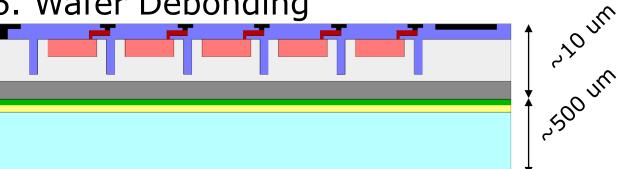




5. Permanent Wafer Bonding









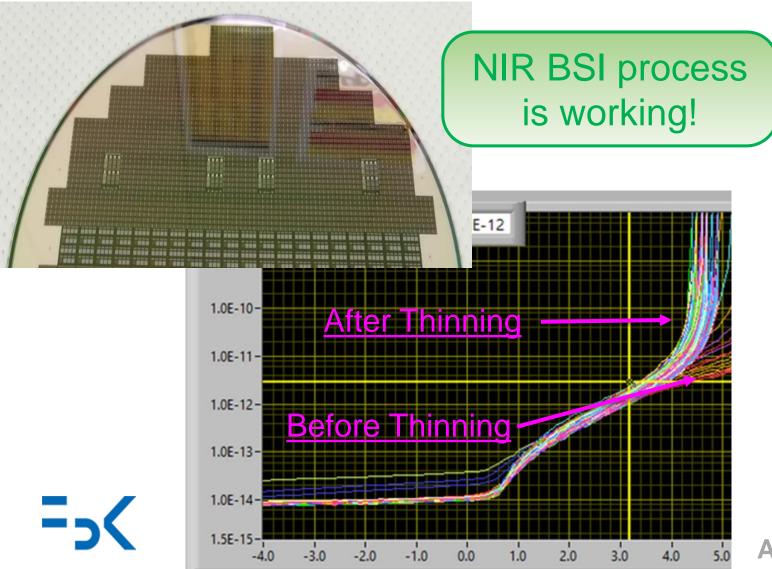
2.5D and 3D Integration BSI SiPMs: first results

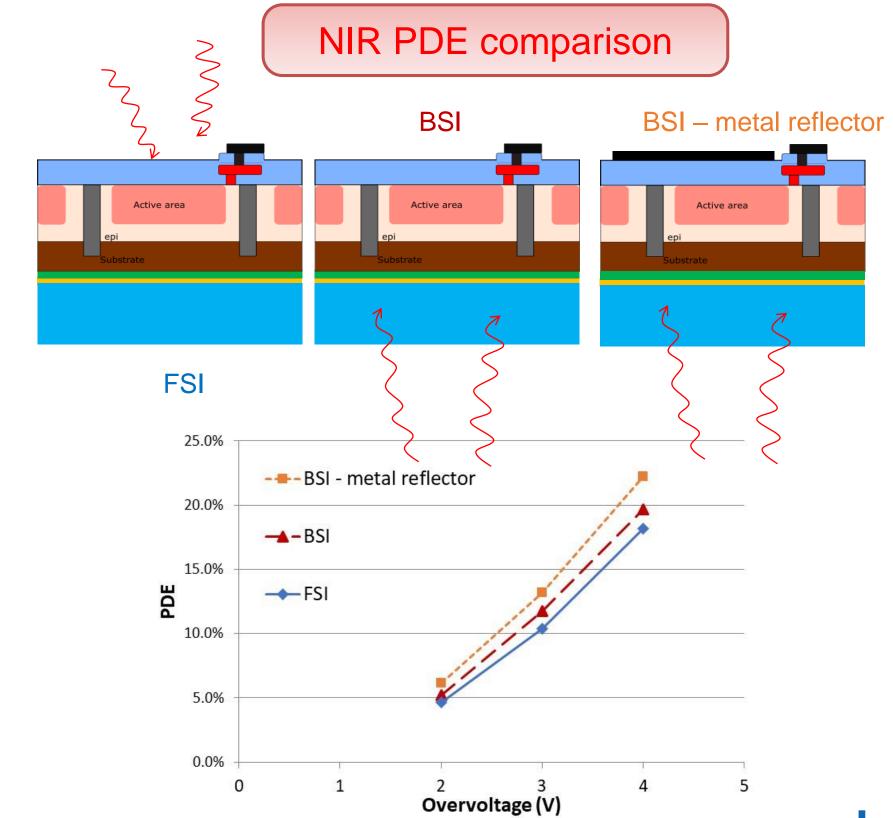
on Microelectronics

The first NIR-sensitive BSI wafers were fabricated in FBK clean room (1x1 mm² devices).

Minor differences in the IVs after thinning, compared to the FSI devices (without thinning).

Ultrathin substrate (~ 10 um)





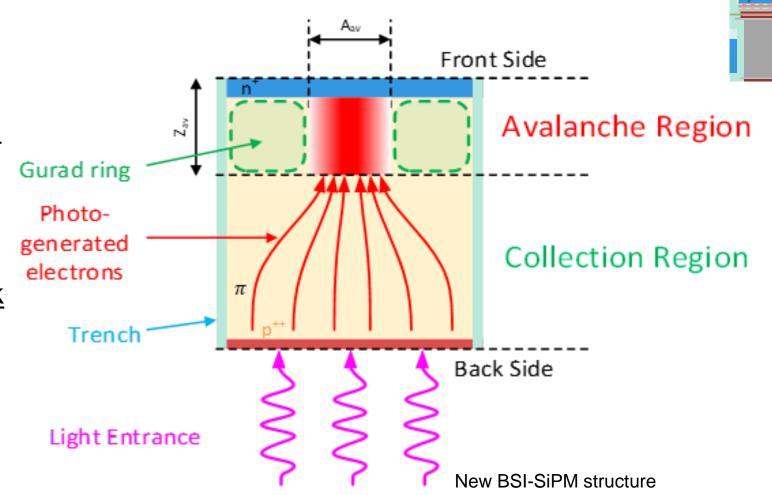
2.5D and 3D Integration Next-generation development: Backside Illuminated SiPMs

The next-generation of developments, currently being investigated at FBK, is building a *backside-illuminated*, *NUV-sensitive SiPM*. Several technological challenges should be overcome.

Clear separation between charge collection and multiplication regions.

Potential Advantages:

- Up to 100% FF even with small cell pitch
- Ultimate <u>Interconnection density</u>: < 15 um
- High speed and dynamic range
- Low gain and external crosstalk
- (Uniform) entrance window on the backside, ideal for <u>enhanced optical stack</u> (VUV sensitivity, nanophotonics)
- <u>Local electronics</u>: ultra fast and possibly low-power.



Development Risks:

10 - 20 um

Charge collection time jitter

Sensor layer (Custom)

Readout layer (CMOS

SPAD array

FEE ASIC

- Low Gain → SPTR?
- Effectiveness of the new entrance window

Radiation hardness:

- The SiPM area sensitive to radiation damage, is much smaller than the light sensitive area
- Assumption: the main source of DCR is field-enhanced generation (or tunneling).



Thank you!

Thanks to all the members of the team working on custom SiPM technology at FBK:

- Fabio Acerbi
- Andrea Ficorella
- Stefano Merzi
- Laura Parellada Monreal
- Elena Moretti
- Giovanni Palù
- Giovanni Paternoster
- Michele Penna
- Maria Ruzzarin
- Tiziano Stedile
- Nicola Zorzi

